FIG. 1A

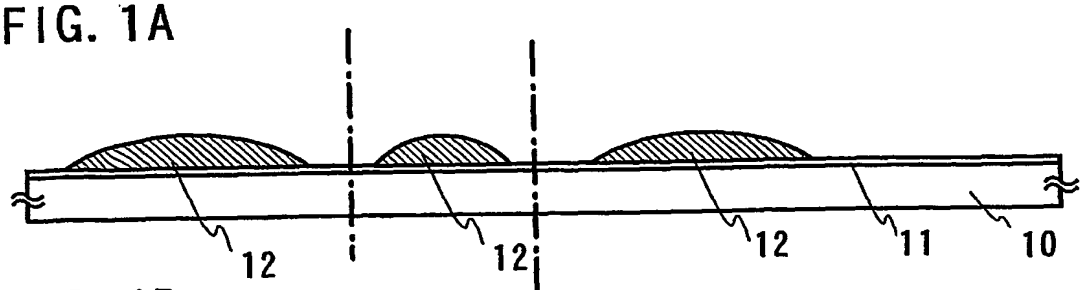


FIG. 1B

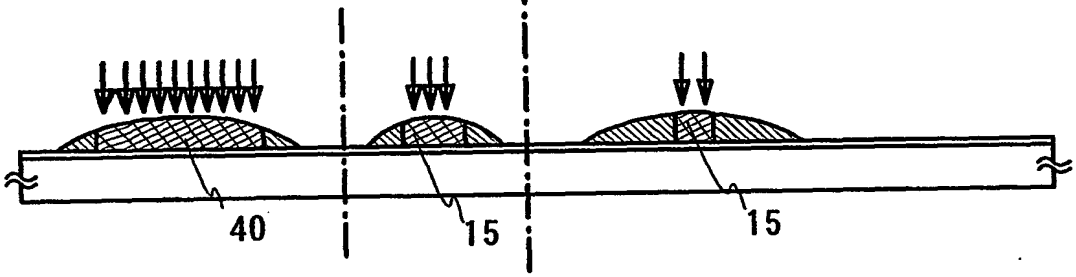


FIG. 1C

FIG. 1D

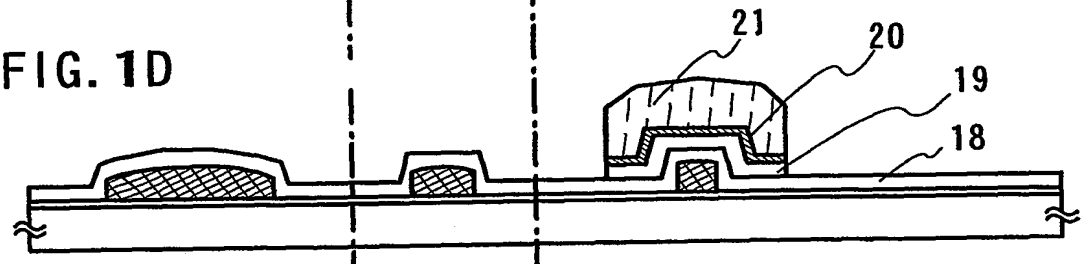


FIG. 1E

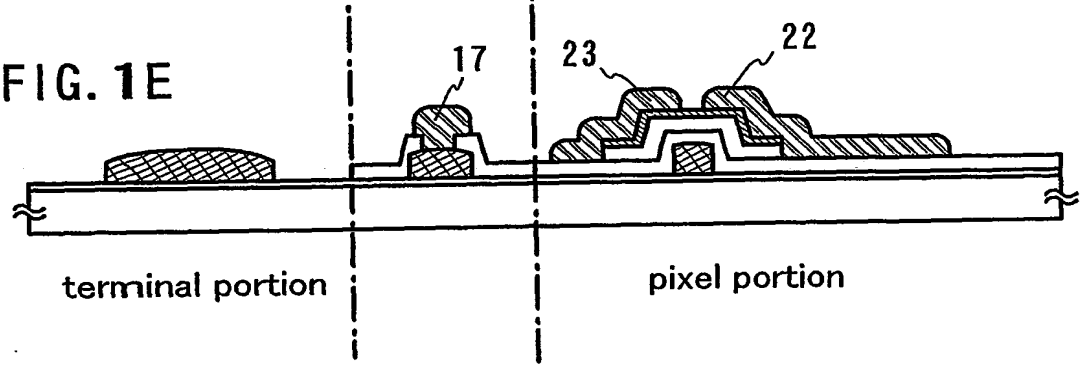


FIG. 2A

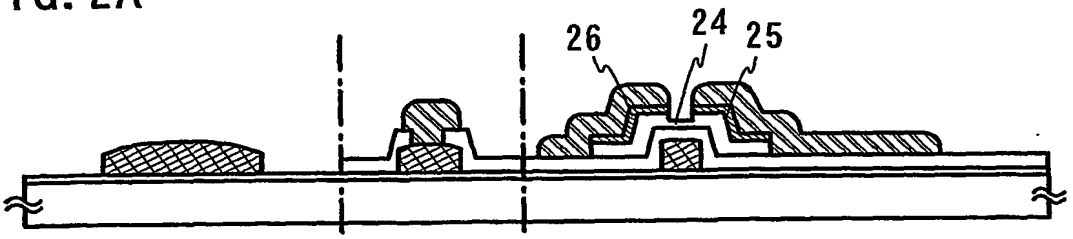


FIG. 2B

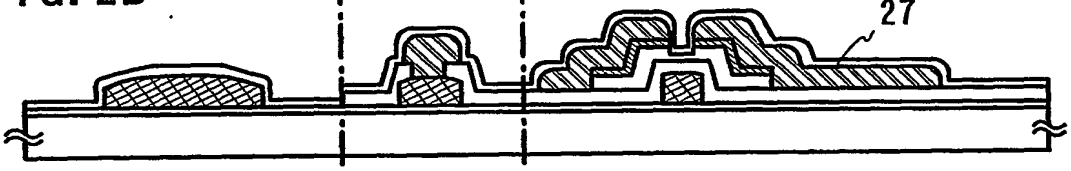


FIG. 2C

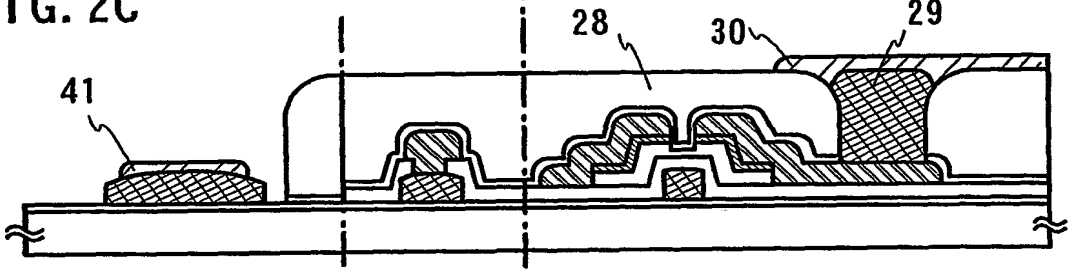


FIG. 2D

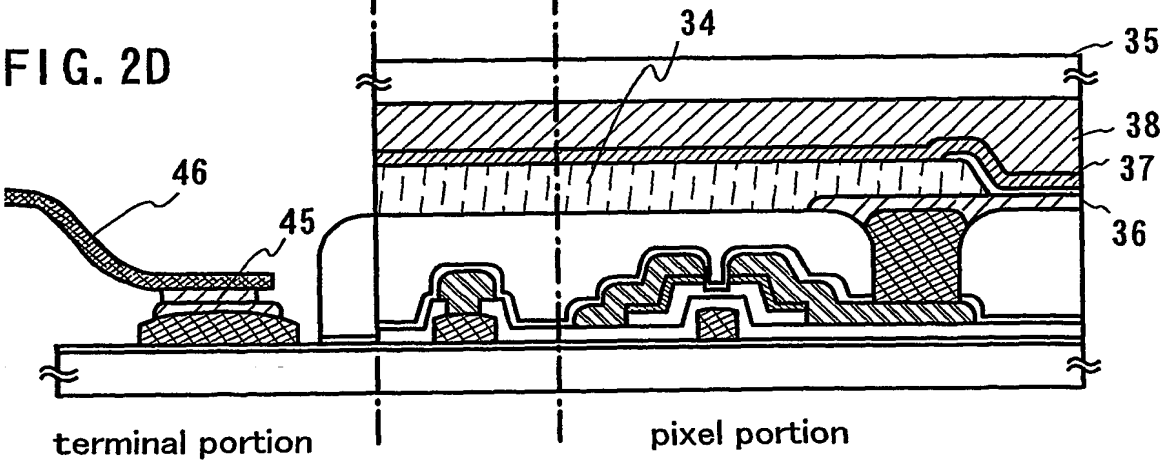


FIG. 3

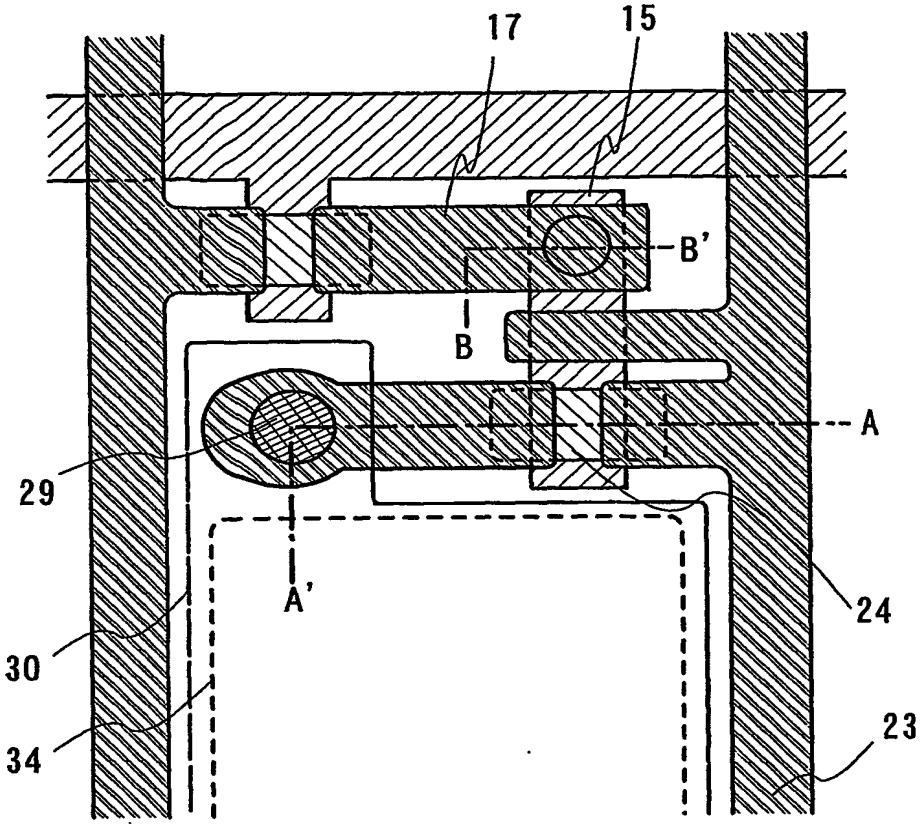


FIG. 4

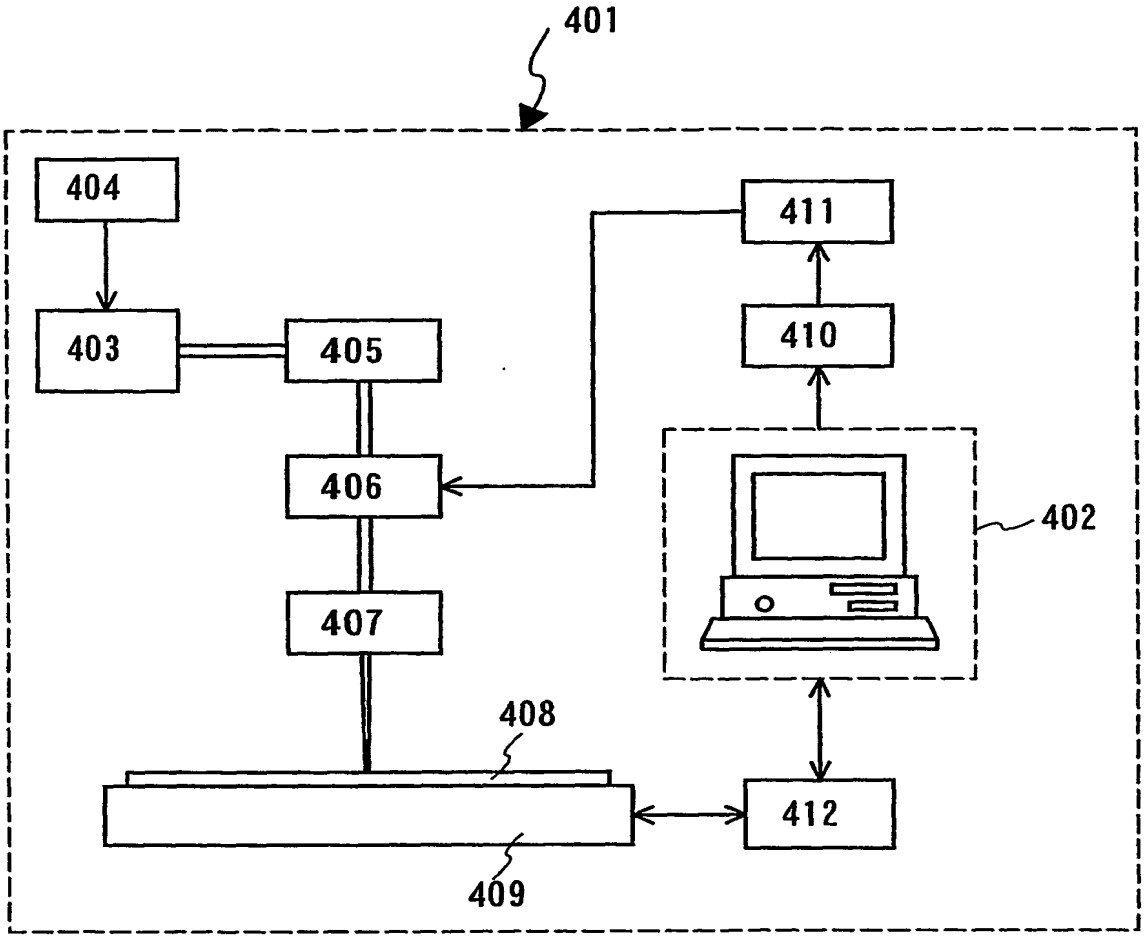


FIG. 5A

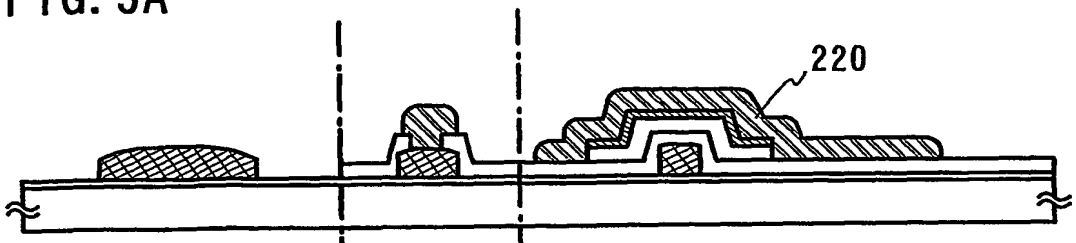


FIG. 5B

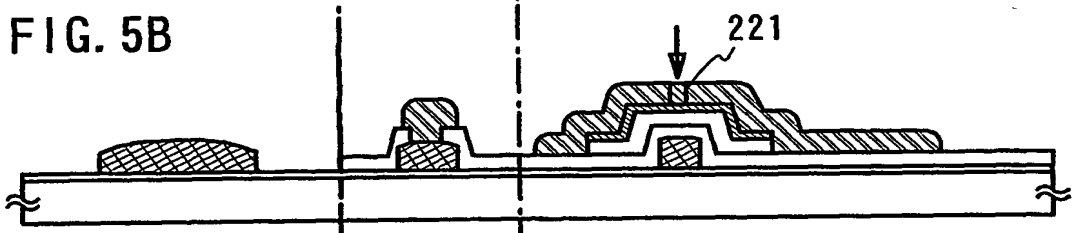


FIG. 5C

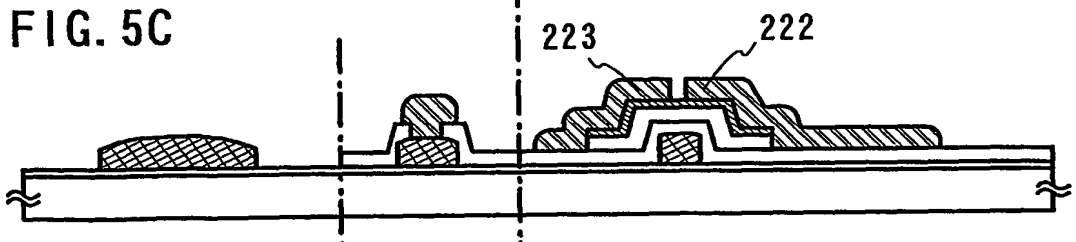
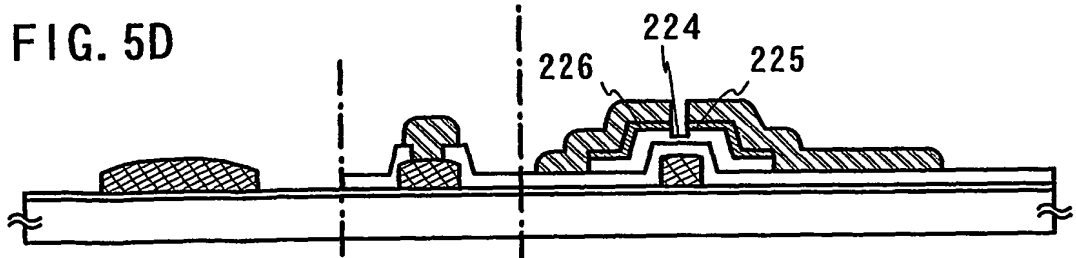


FIG. 5D



terminal portion

pixel portion

FIG. 6A

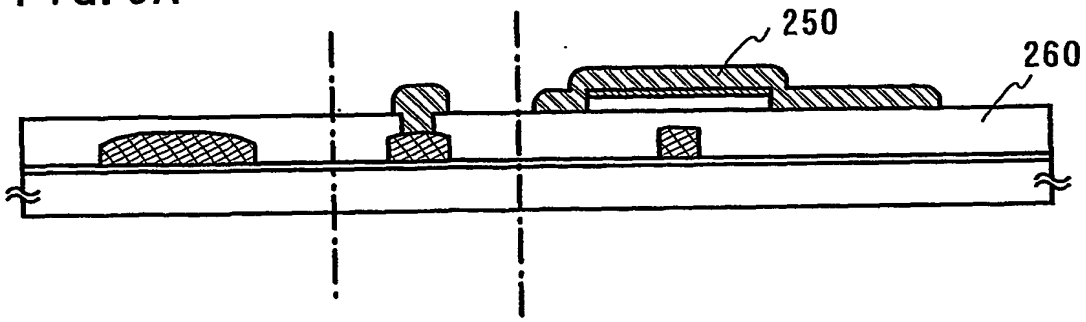


FIG. 6B

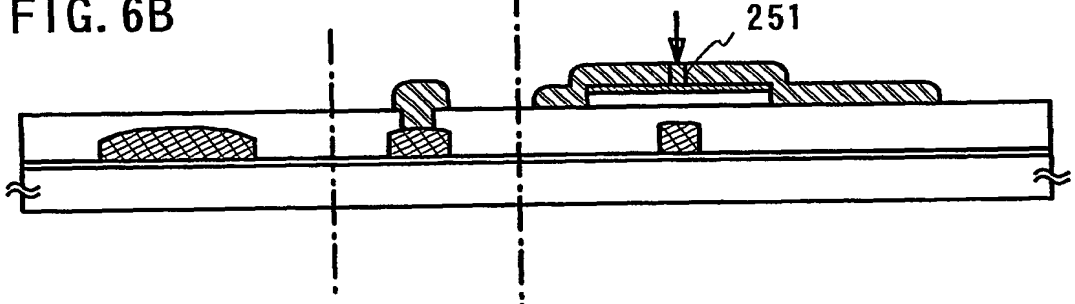


FIG. 6C

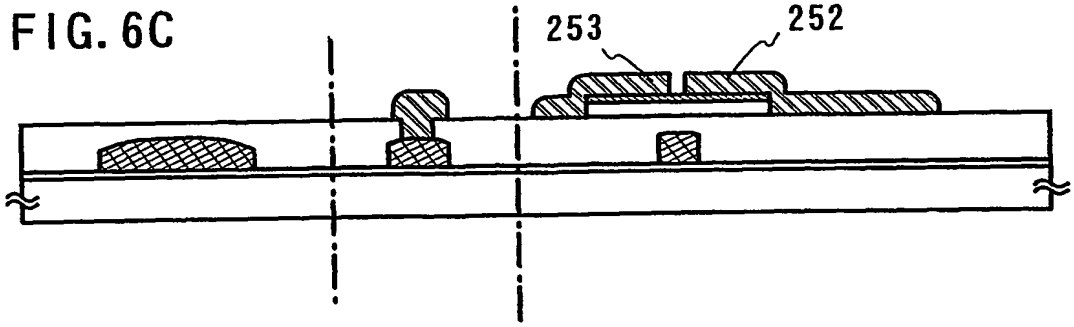


FIG. 6D

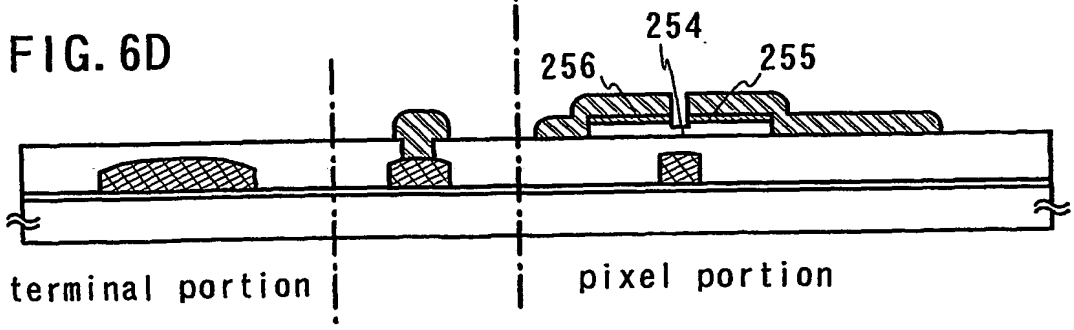


FIG. 7A

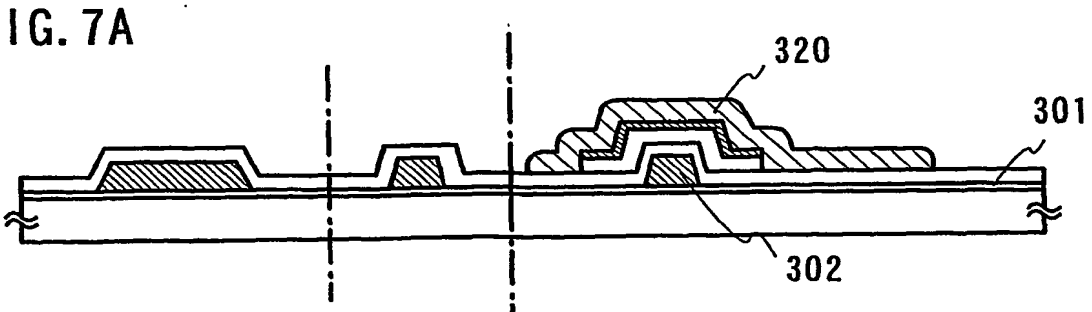


FIG. 7B

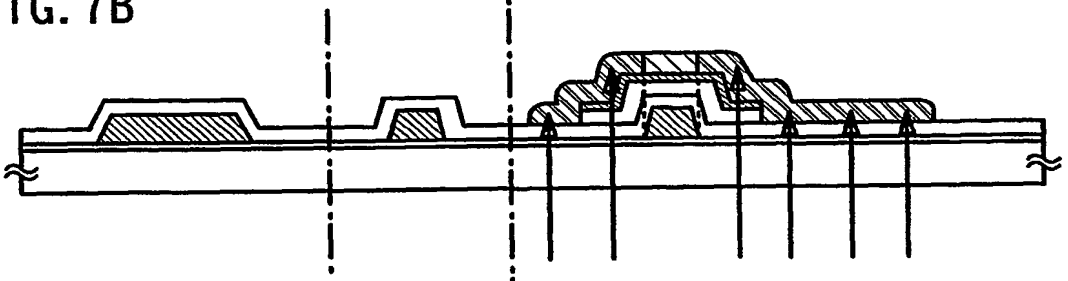


FIG. 7C

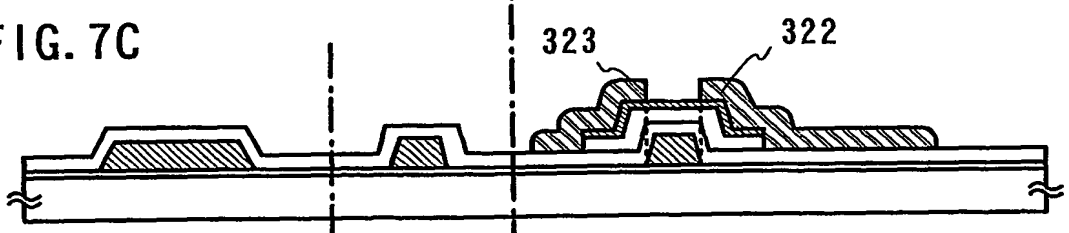


FIG. 7D

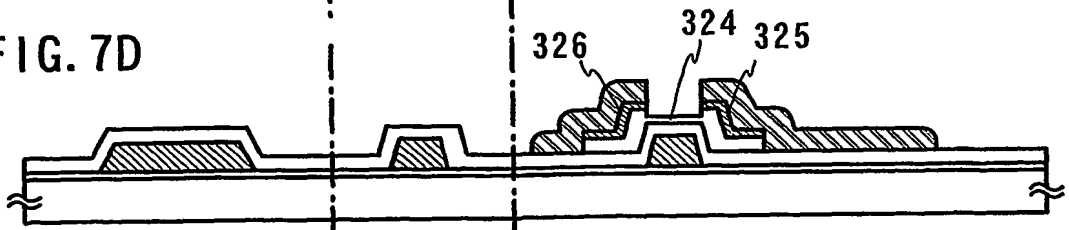


FIG. 8

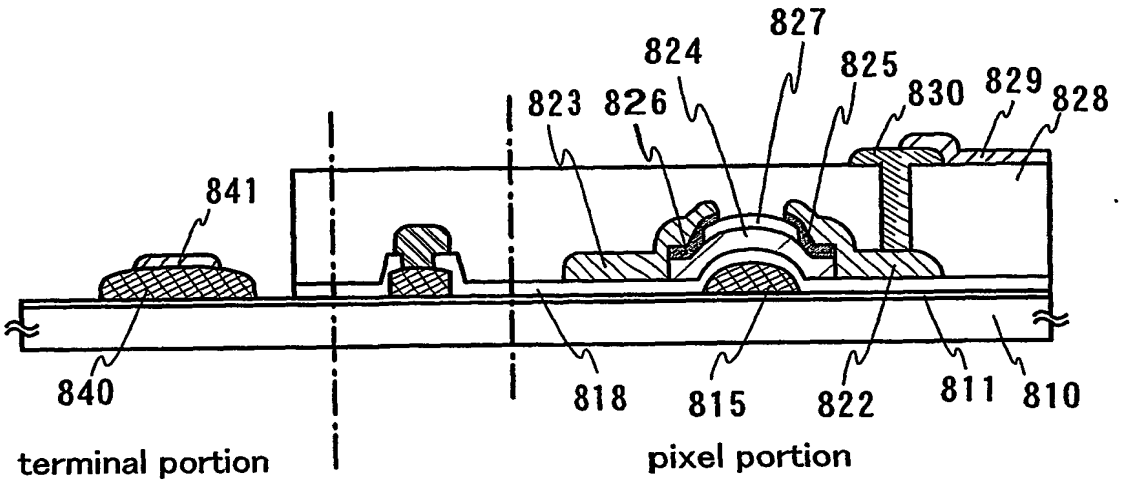

827
824
825
823
826
830
829
828
841
840
818
815
822
811
810
terminal portion
pixel portion

FIG. 9

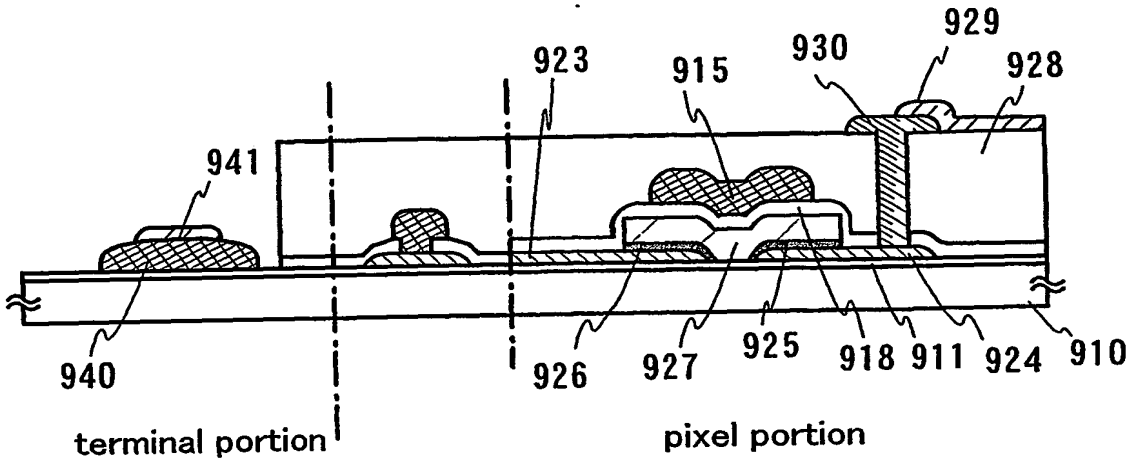

929
923
915
930
928
941
940
926
927
925
918
911
924
910
terminal portion
pixel portion

FIG. 10

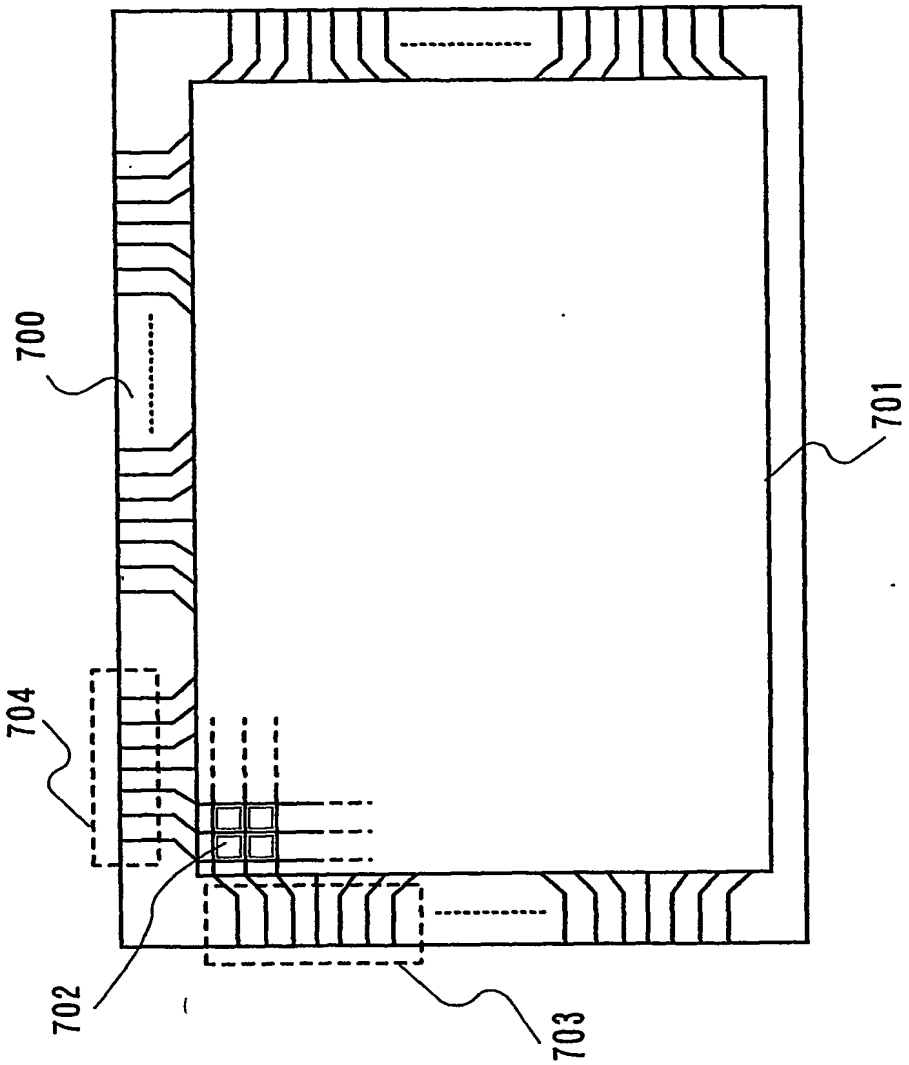


FIG. 11

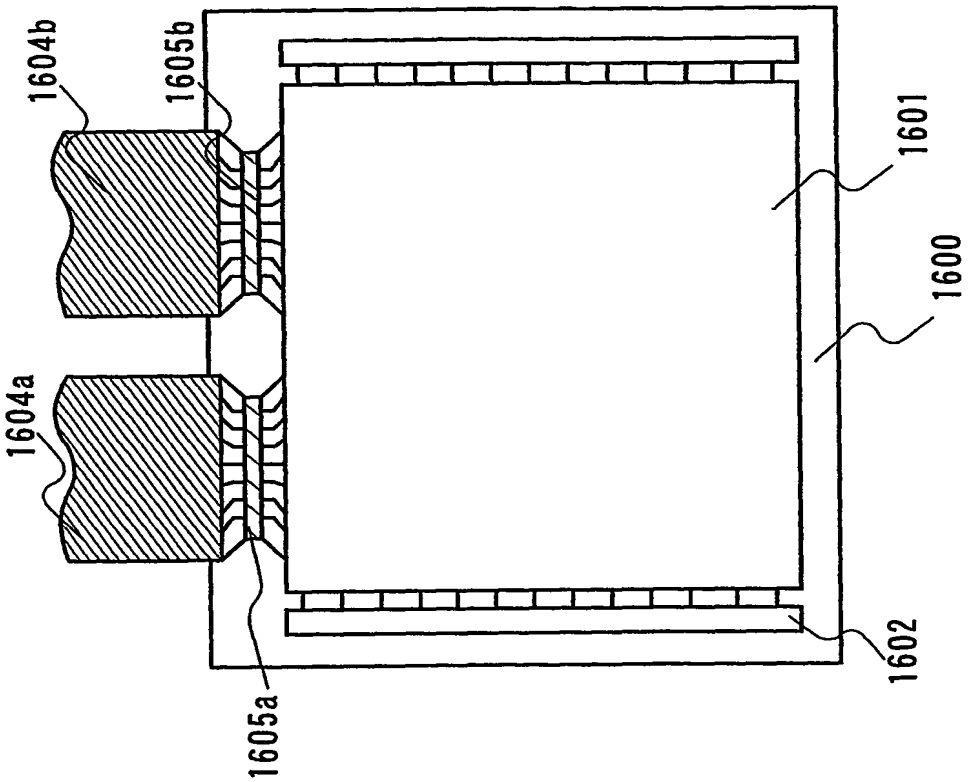


FIG. 12A

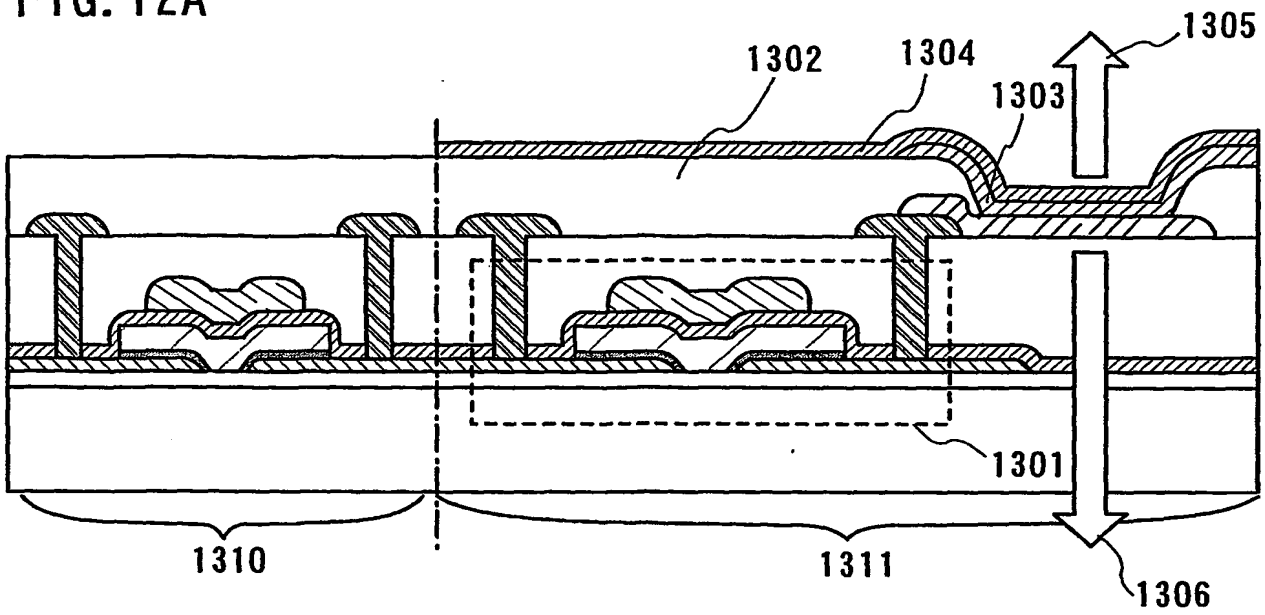


FIG. 12B

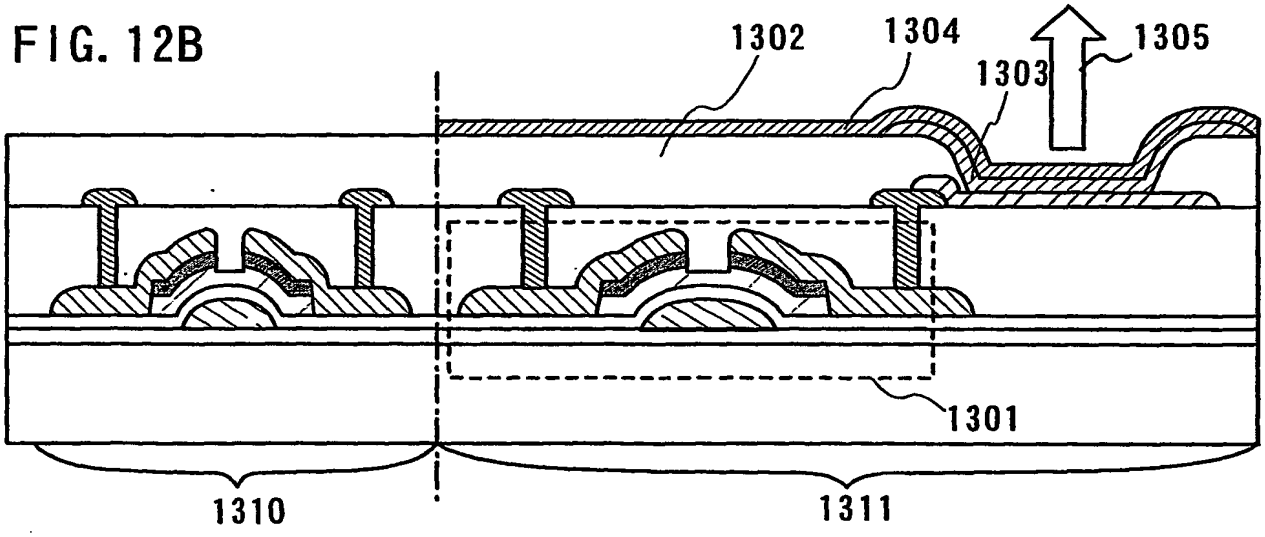


FIG. 12C

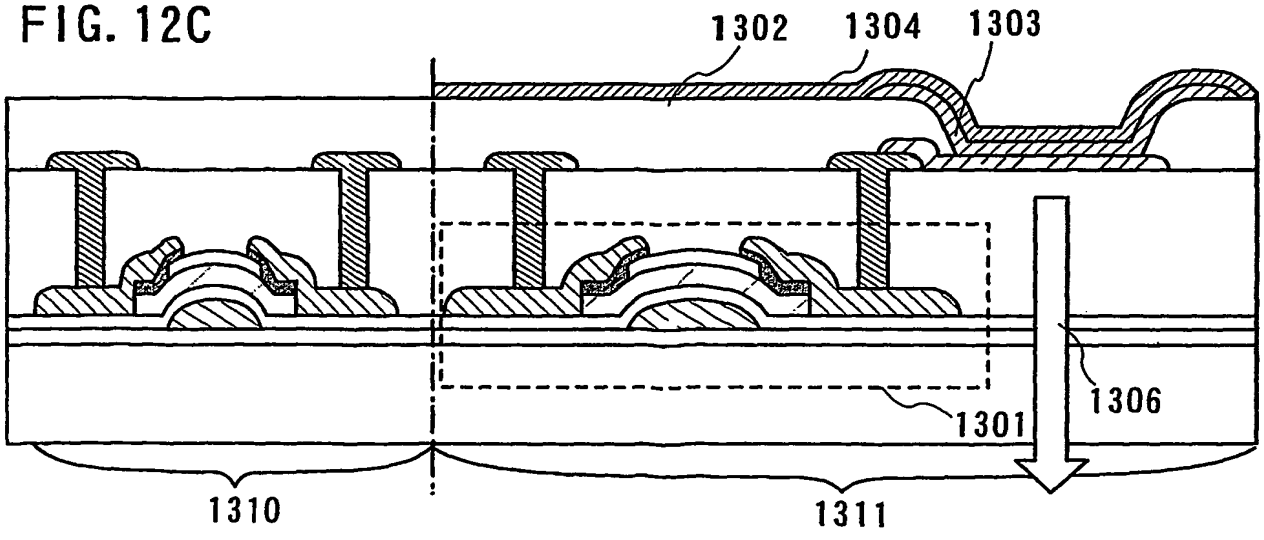


FIG. 13A

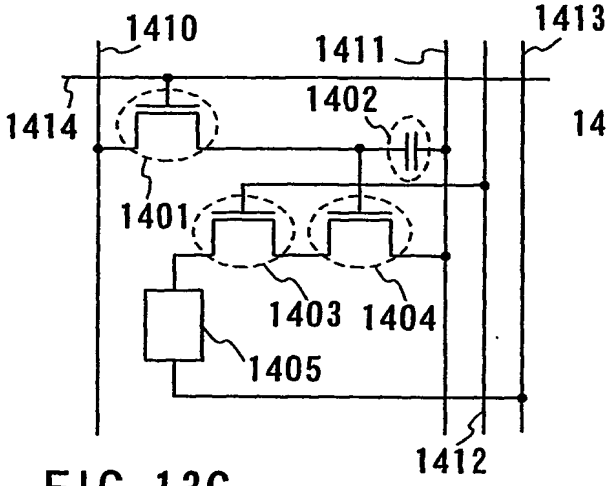


FIG. 13B

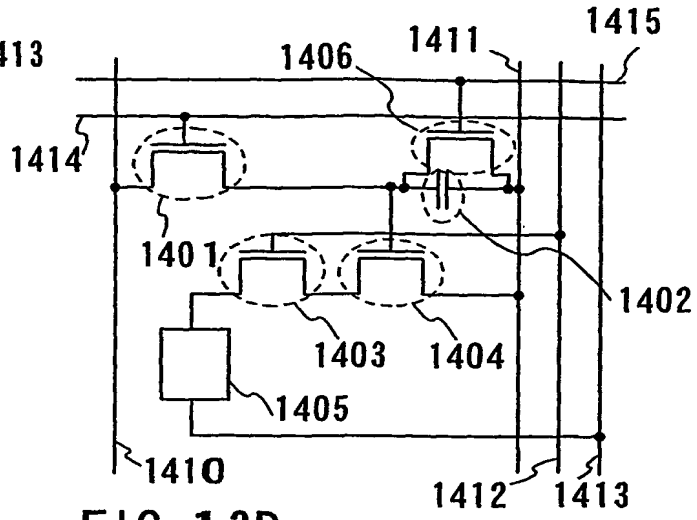


FIG. 13C

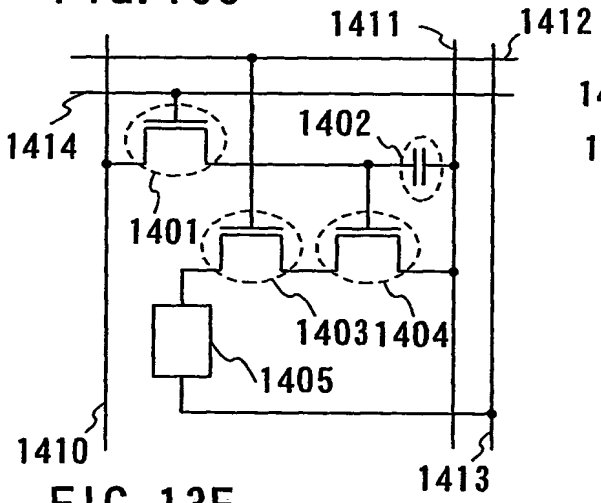


FIG. 13D

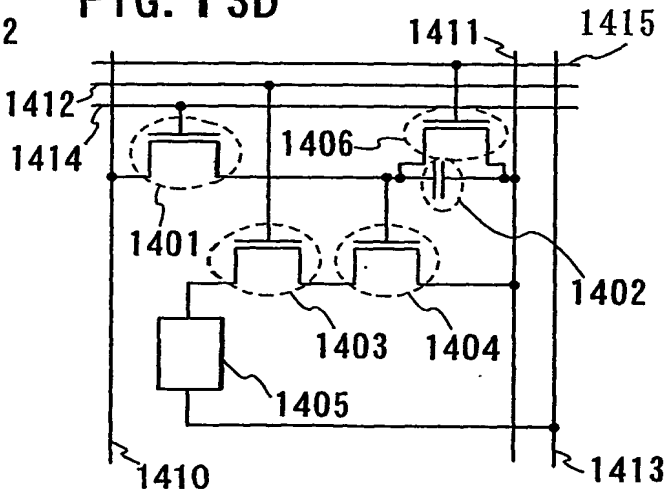


FIG. 13E

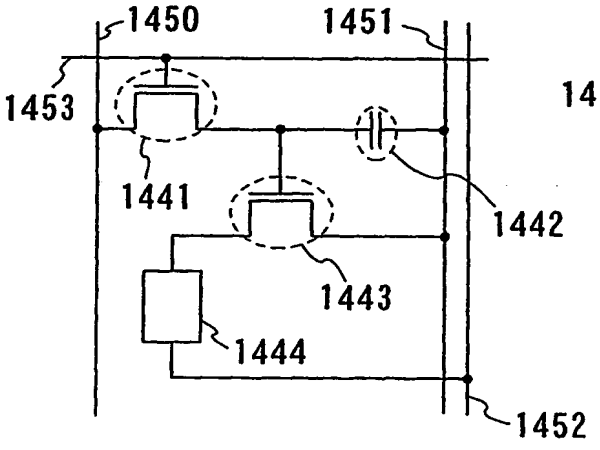


FIG. 13F

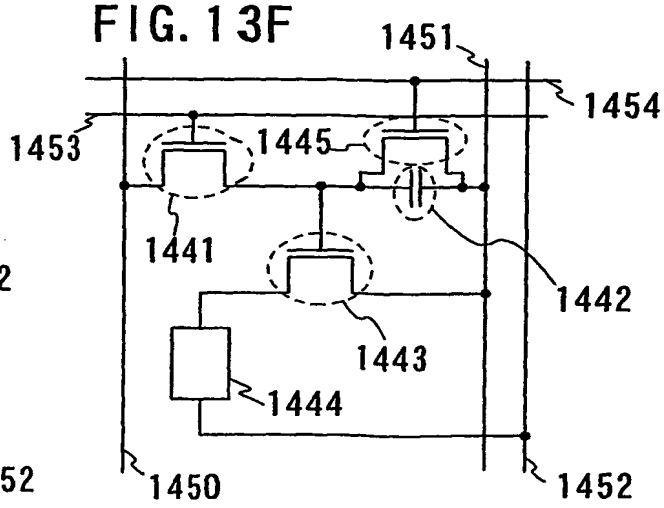


FIG. 14A

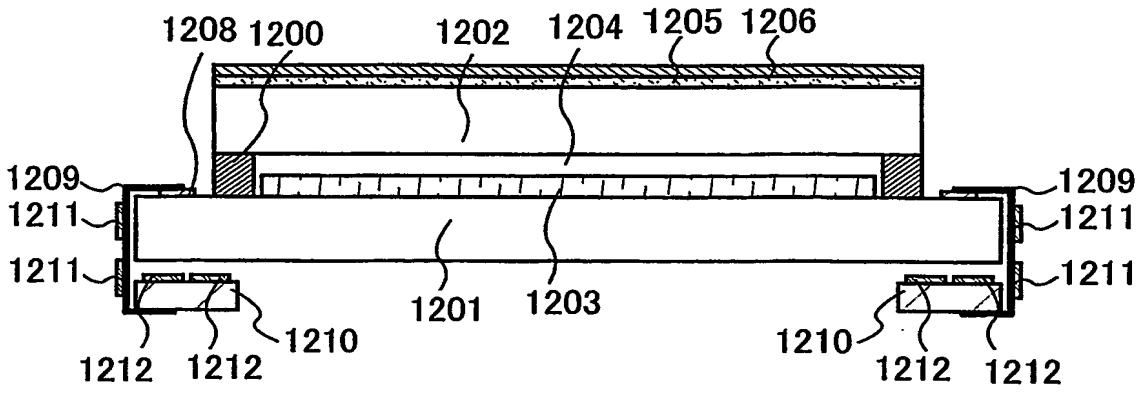


FIG. 14B

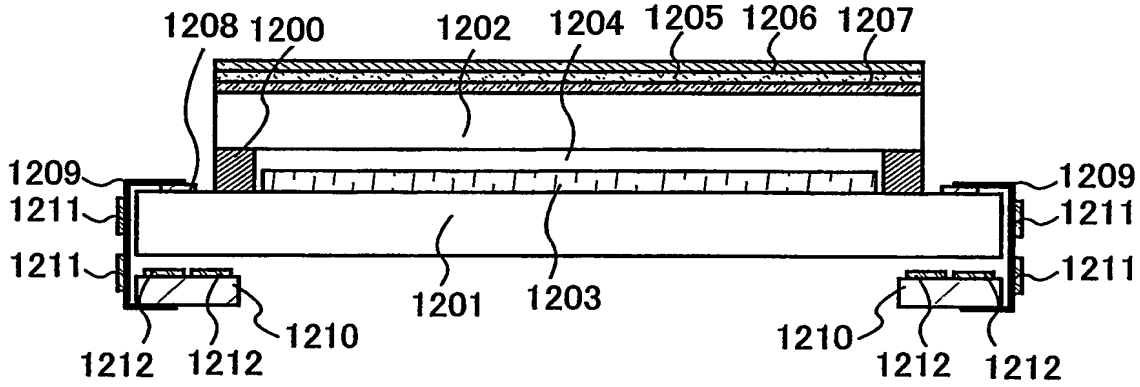


FIG. 14C

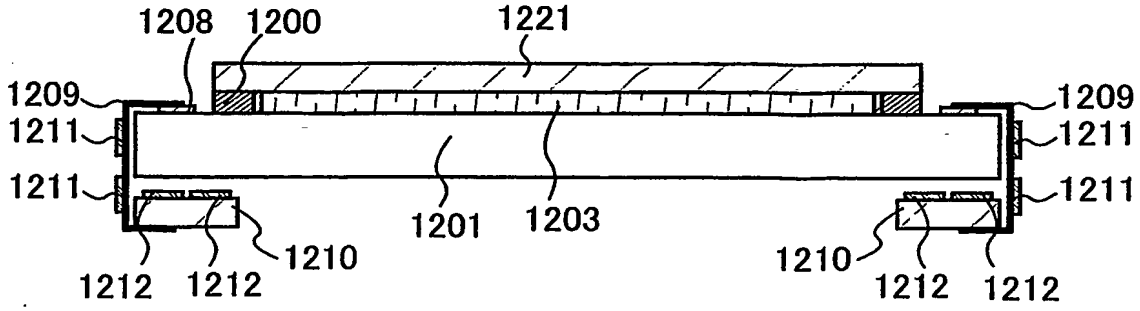


FIG. 15A

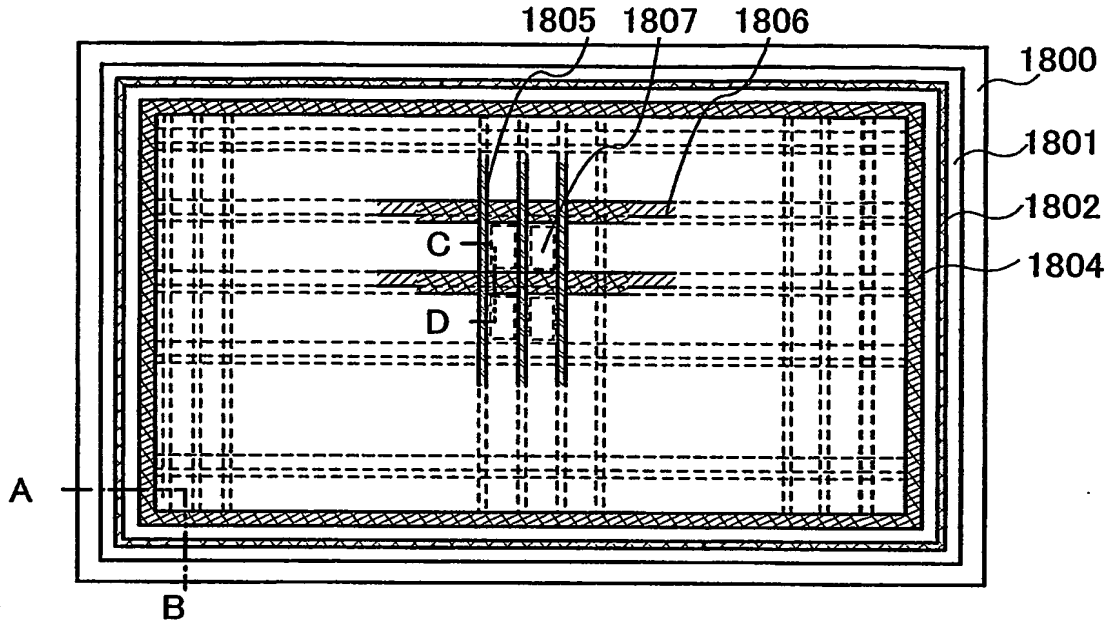


FIG. 15B

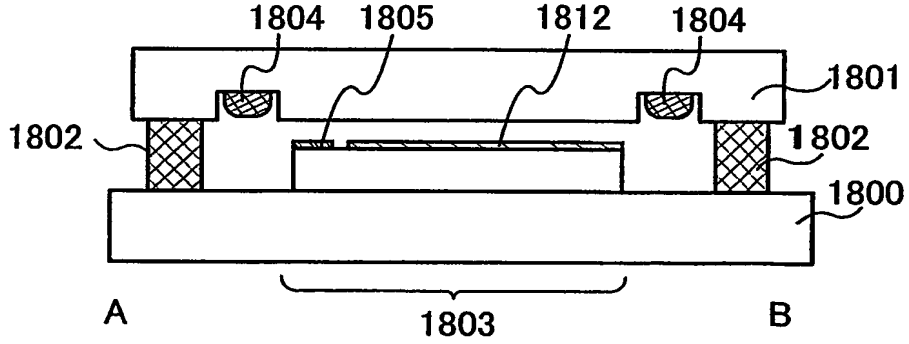


FIG. 15C

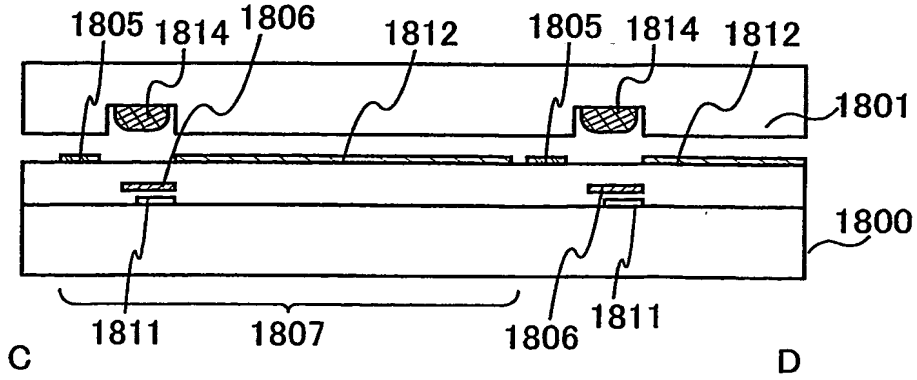


FIG. 16

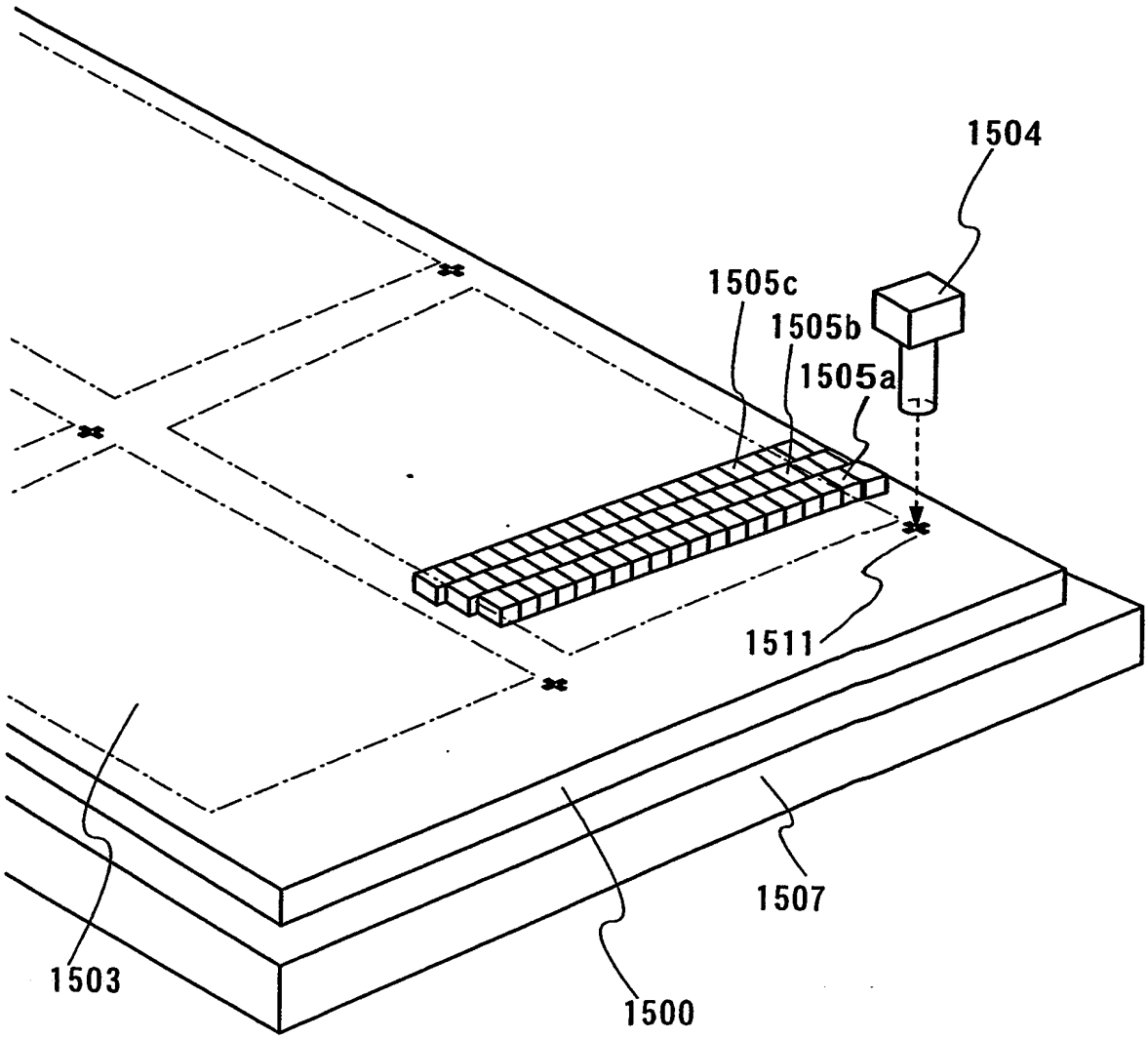


FIG. 17A

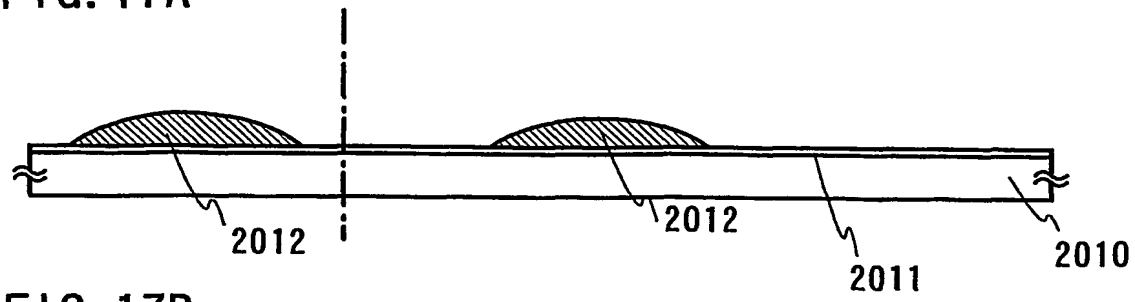


FIG. 17B

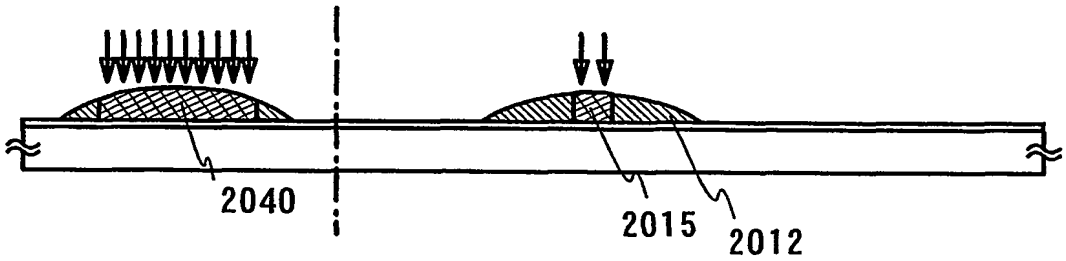


FIG. 17C

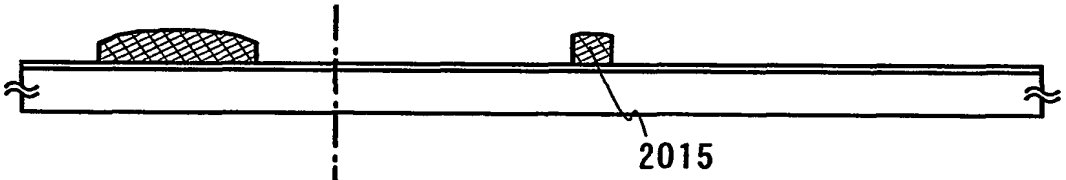


FIG. 17D

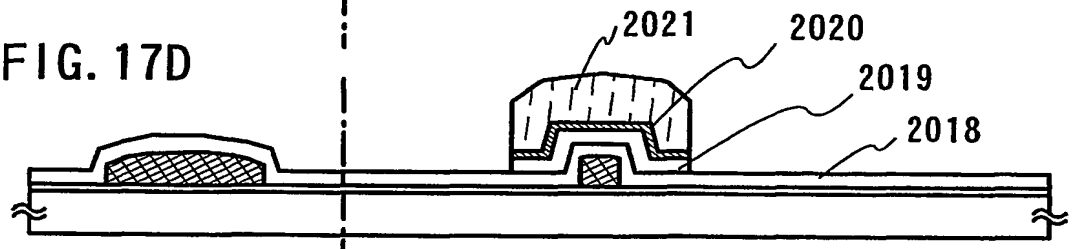
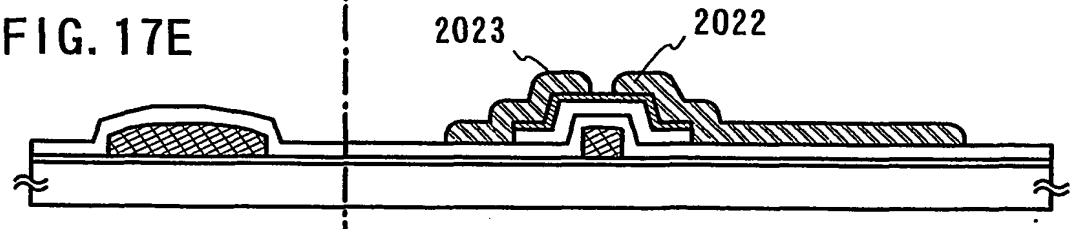


FIG. 17E



terminal portion pixel portion

FIG. 18A

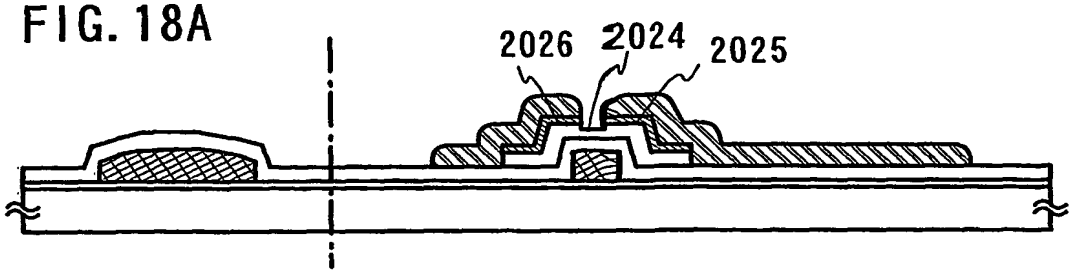


FIG. 18B

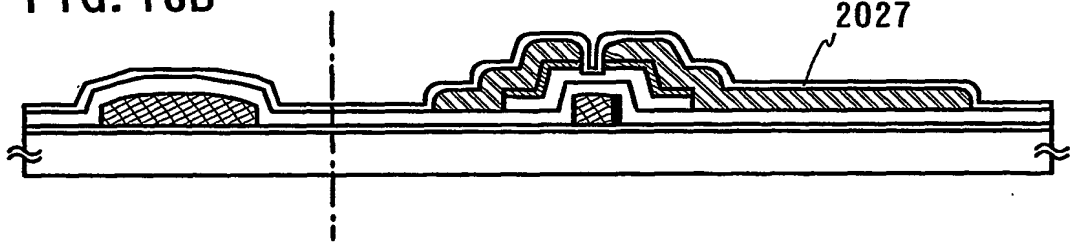


FIG. 18C

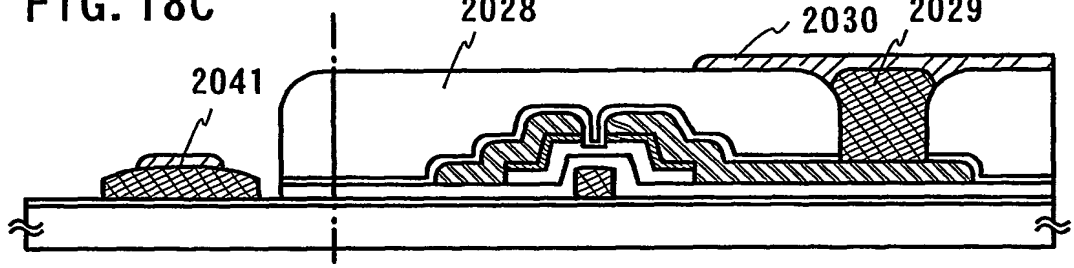
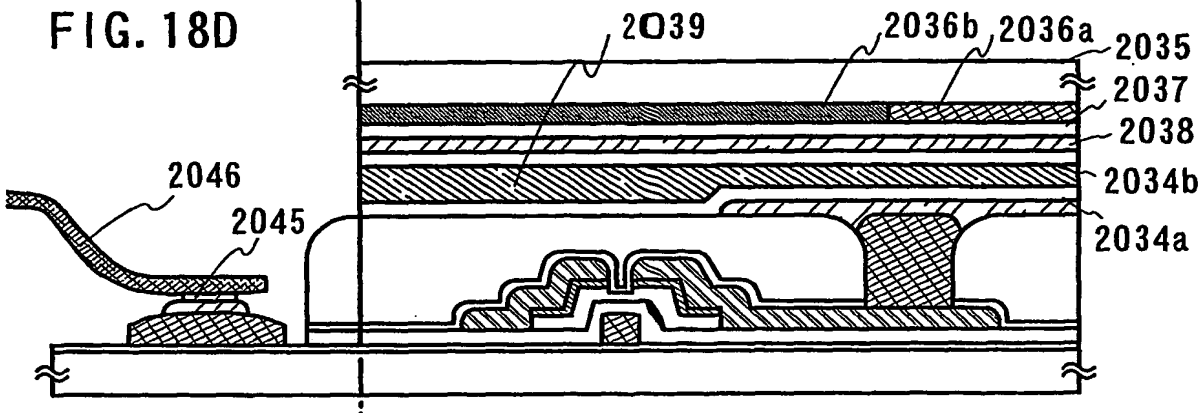


FIG. 18D



terminal portion pixel portion

FIG. 19

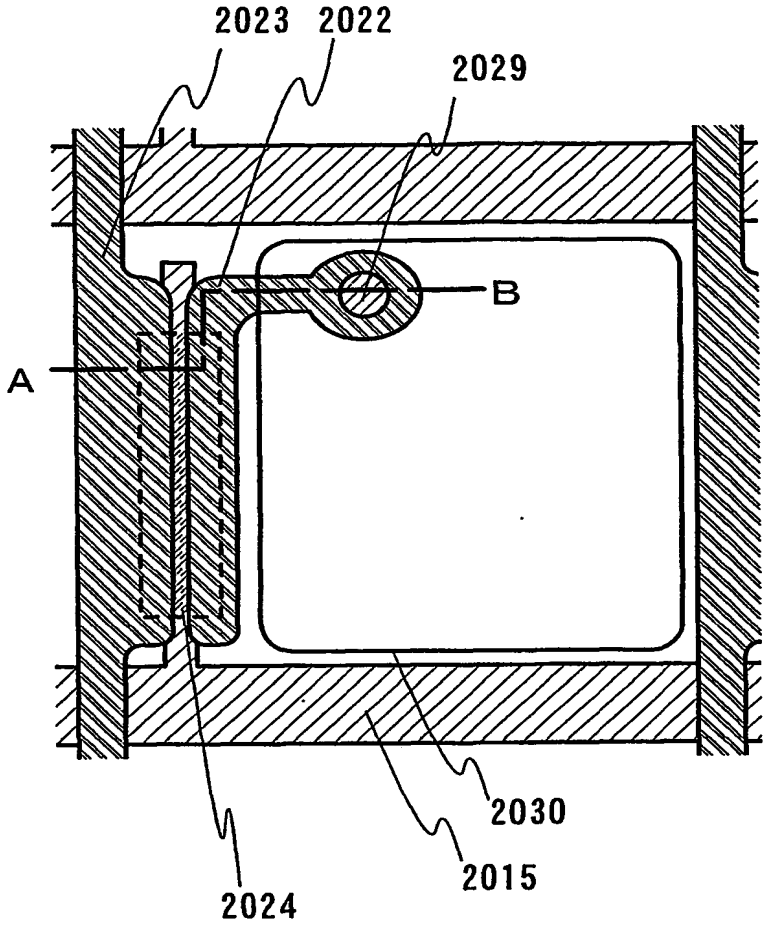


FIG. 20A

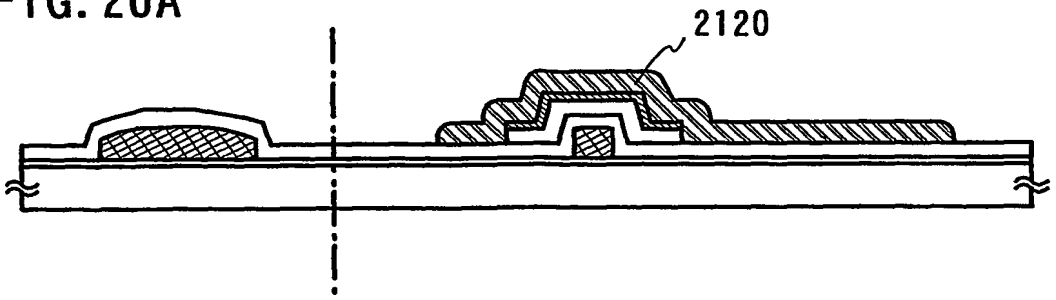


FIG. 20B

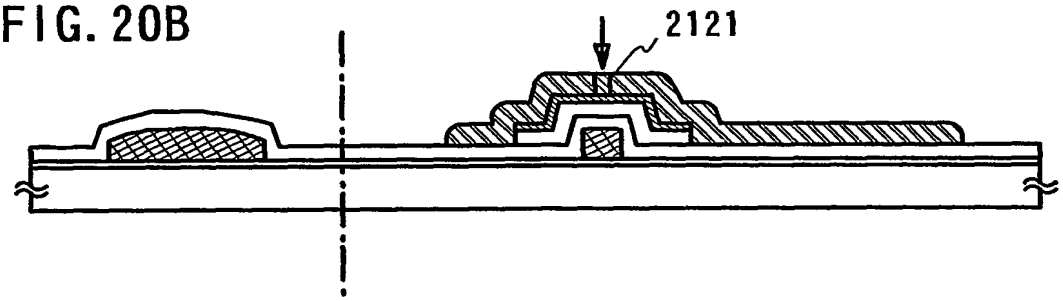


FIG. 20C

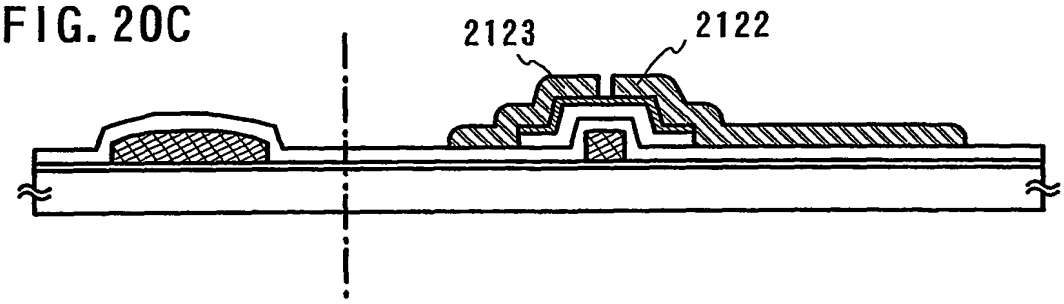


FIG. 20D

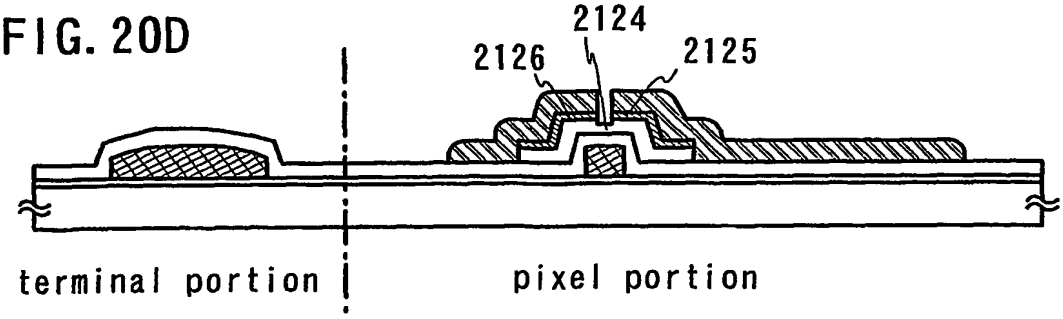


FIG. 21A

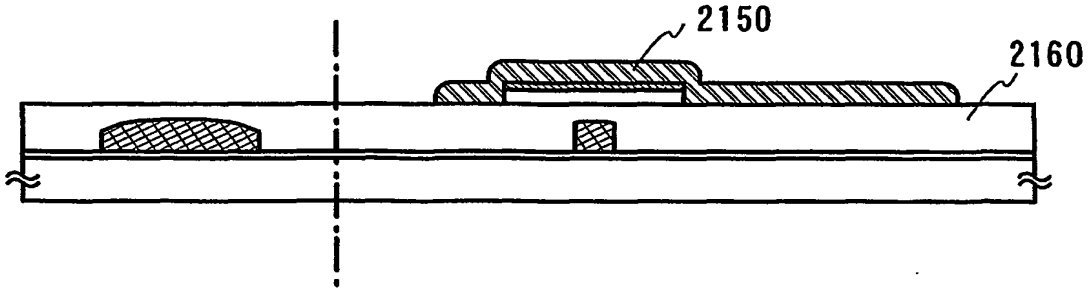


FIG. 21B

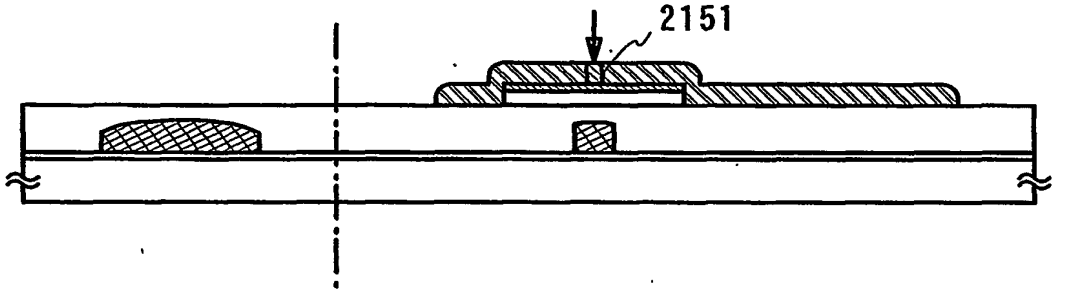


FIG. 21C

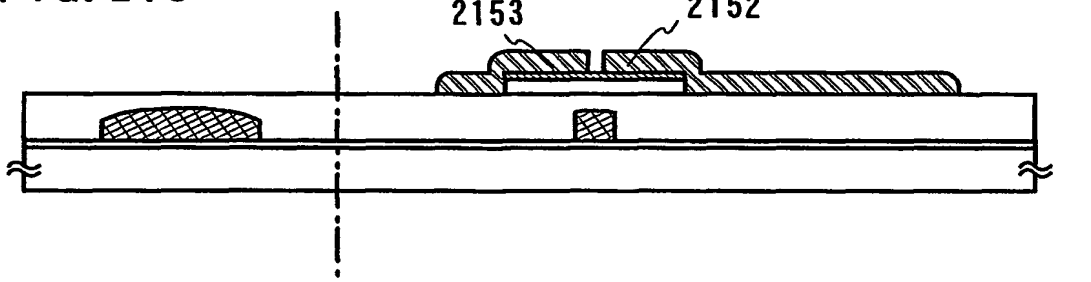


FIG. 21D

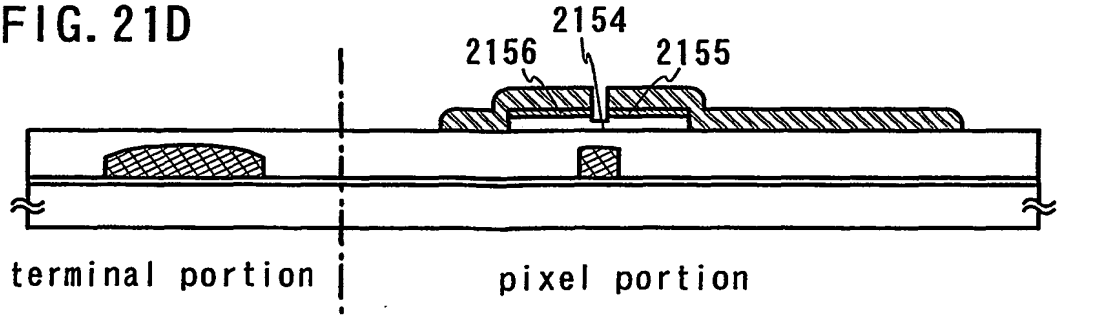


FIG. 22A

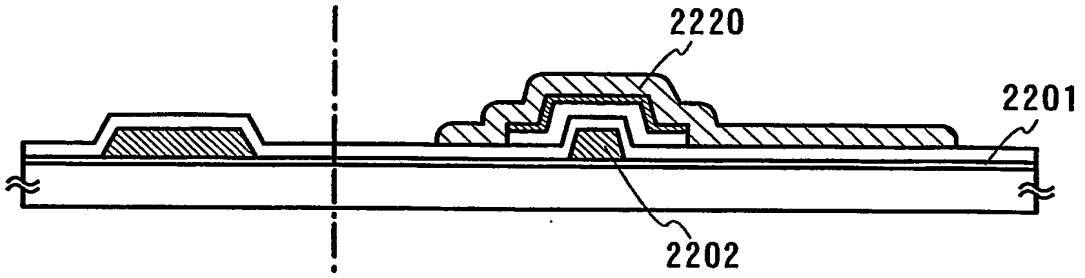


FIG. 22B

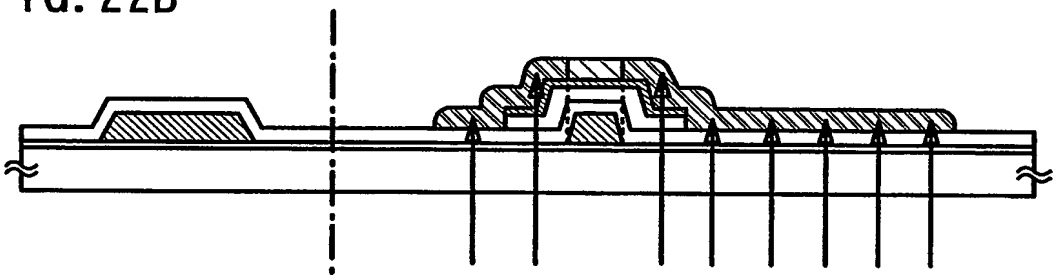


FIG. 22C

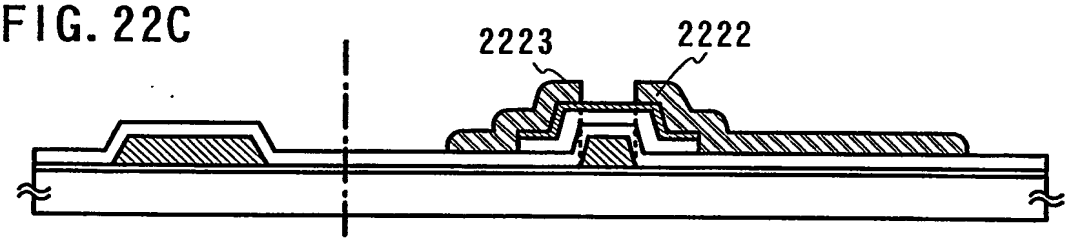


FIG. 22D

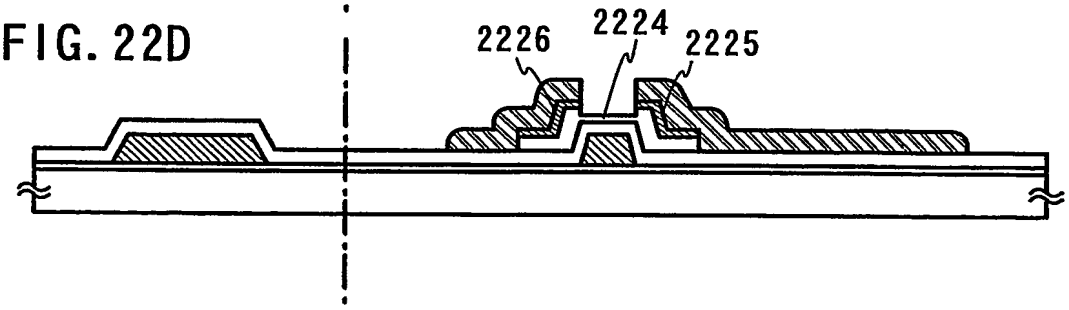


FIG. 23

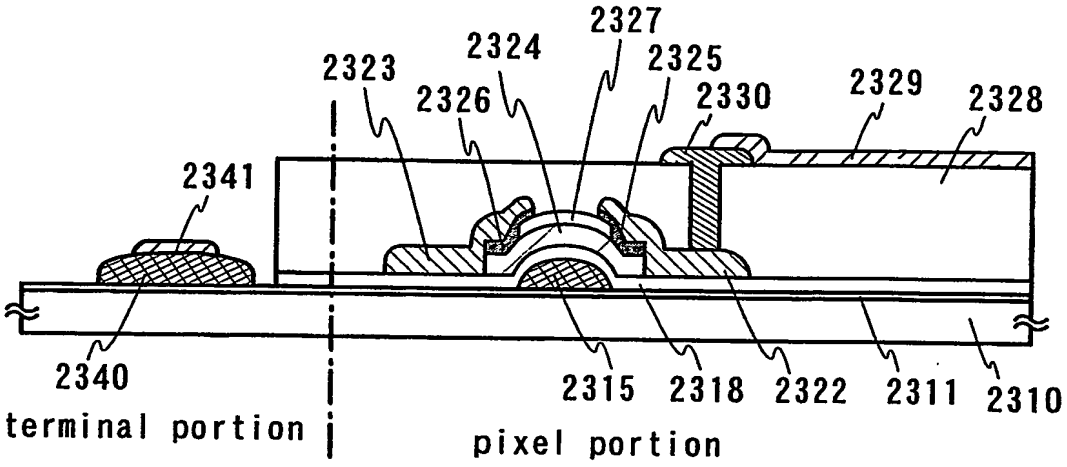

2327
2324
2323
2325
2326
2330
2329
2328
2341
2340
2315
2318
2322
2311
2310
terminal portion
pixel portion

FIG. 24

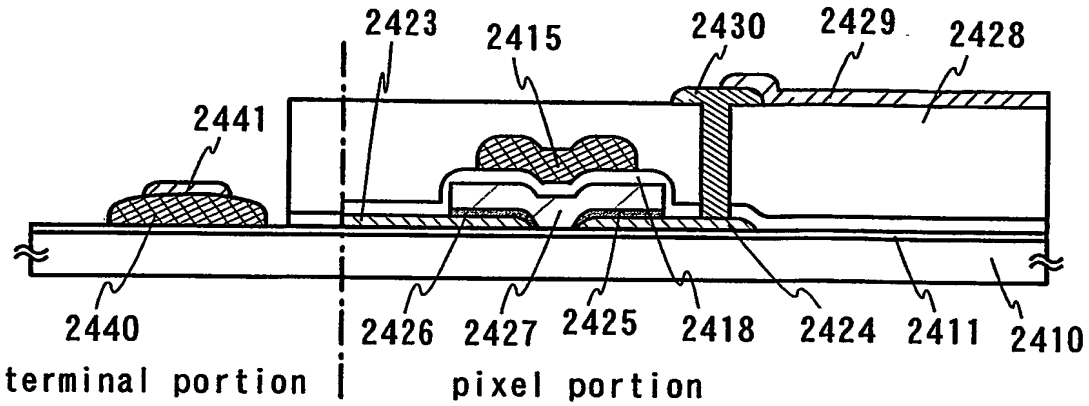

2423
2415
2430
2429
2428
2441
2440
2426
2427
2425
2418
2424
2411
2410
terminal portion
pixel portion

FIG. 25A

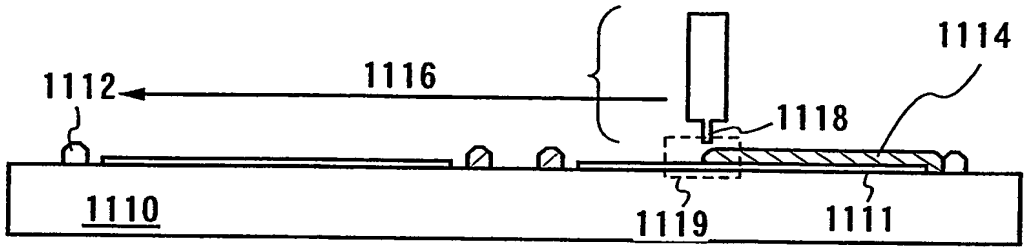


FIG. 25B

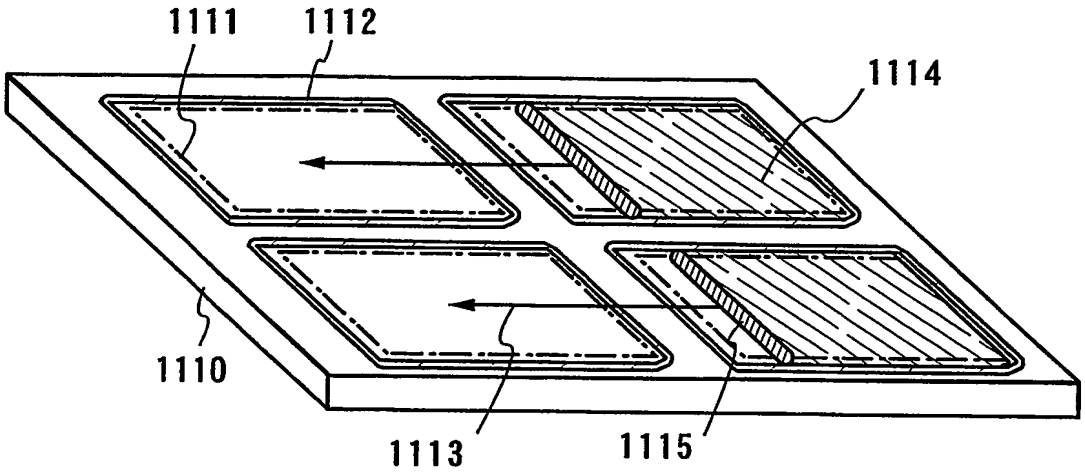


FIG. 25C

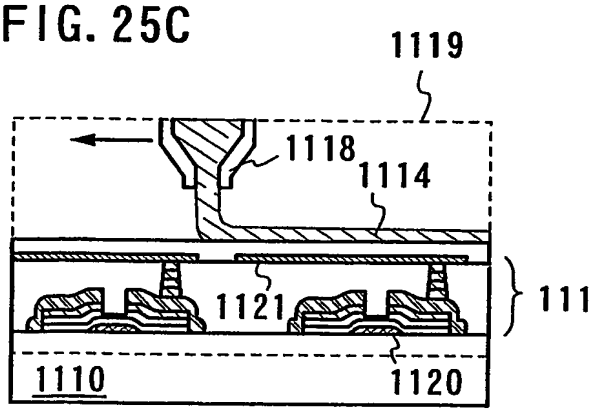


FIG. 25D

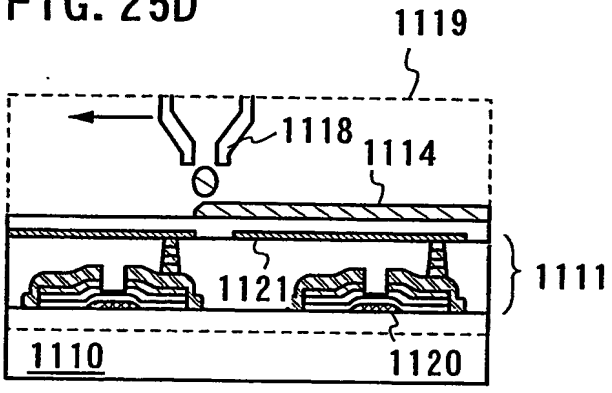


FIG. 26A

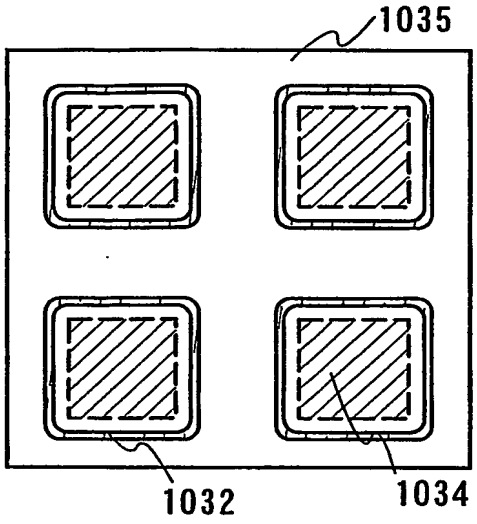


FIG. 26B

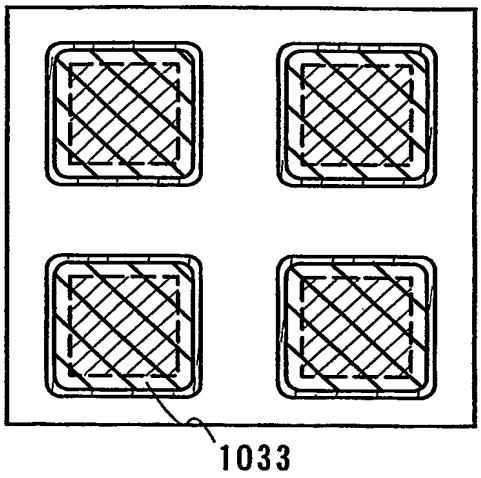


FIG. 26C

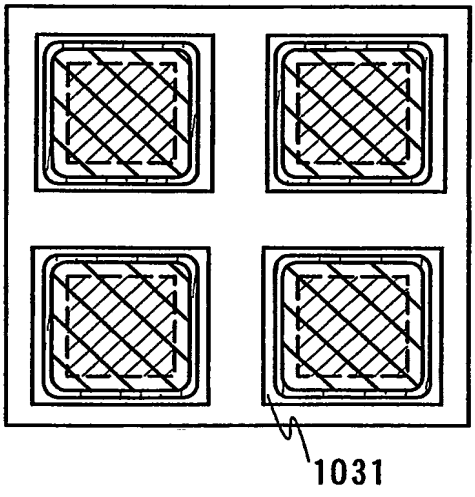


FIG. 26D

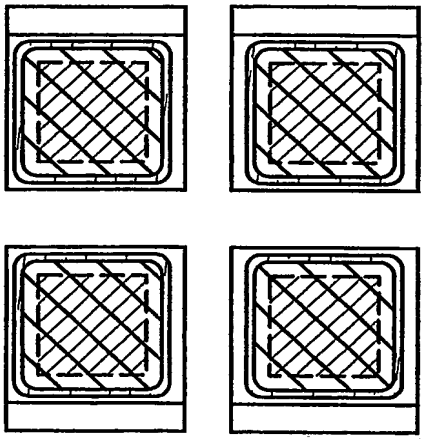


FIG. 27A

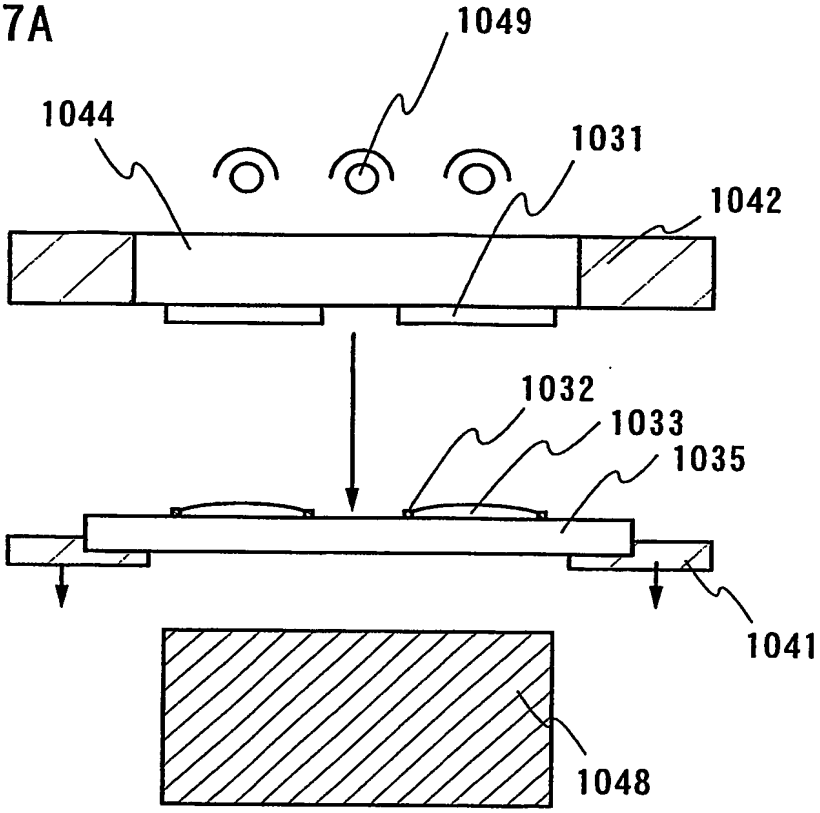


FIG. 27B

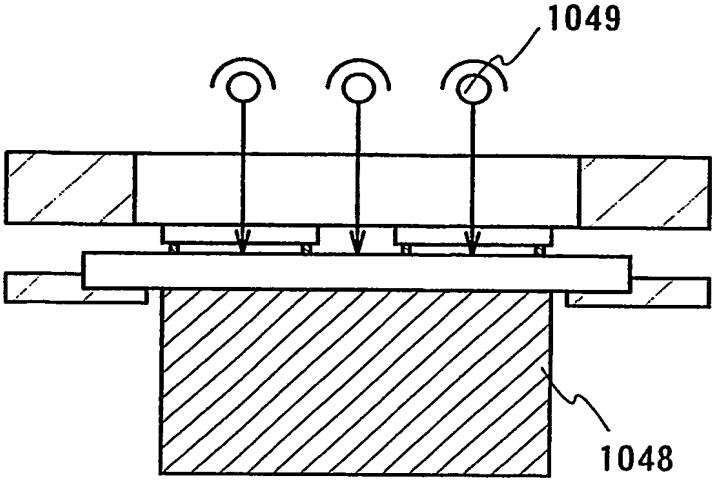


FIG. 28A

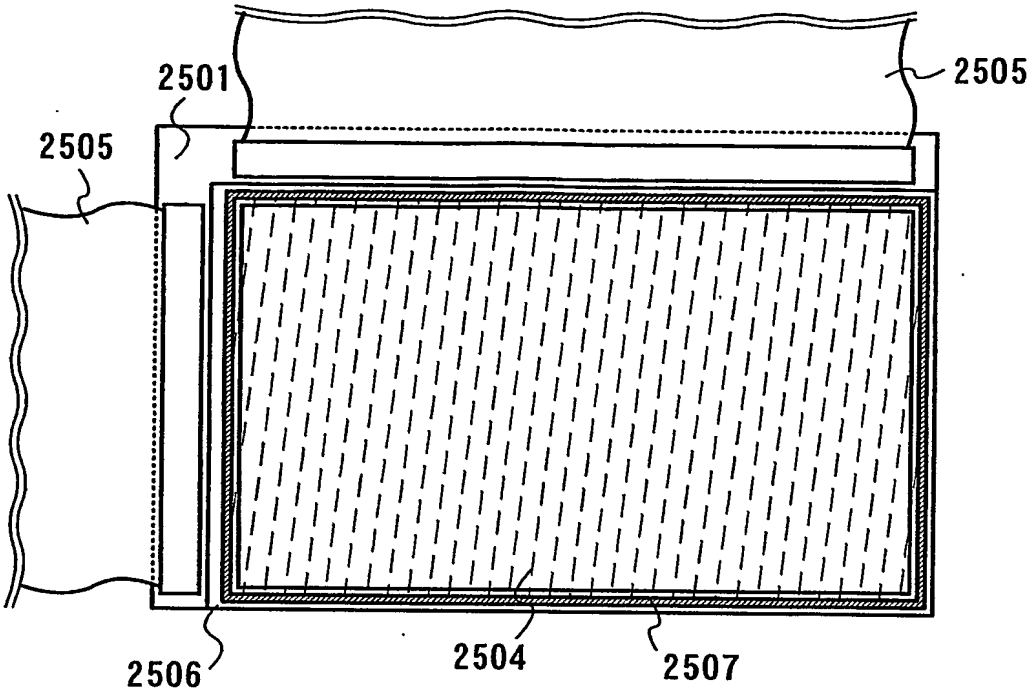


FIG. 28B

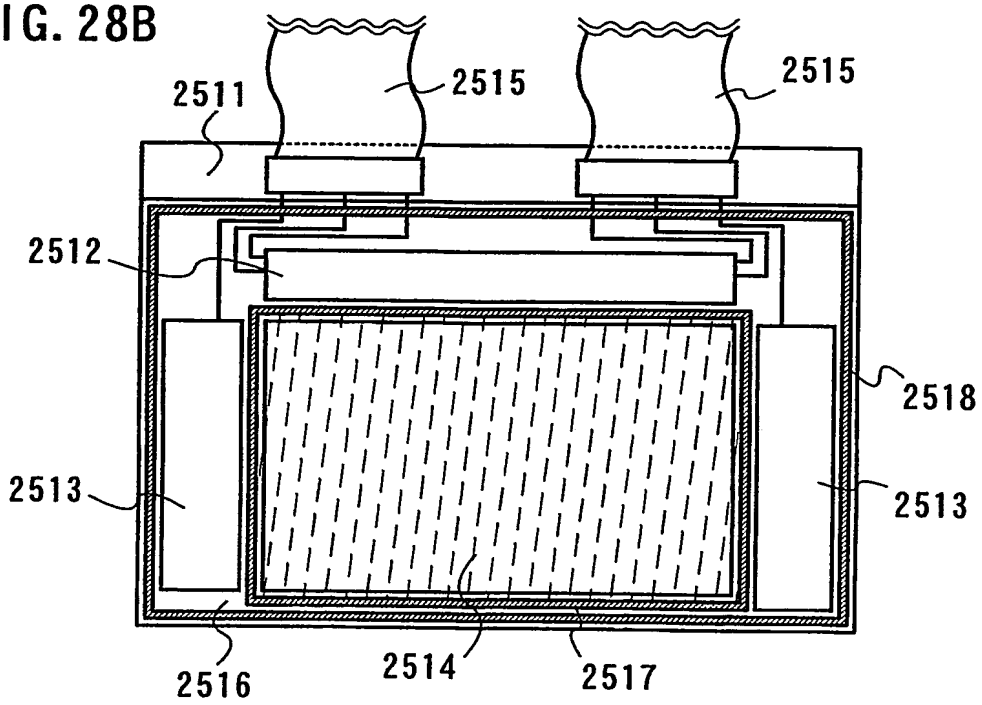


FIG. 29

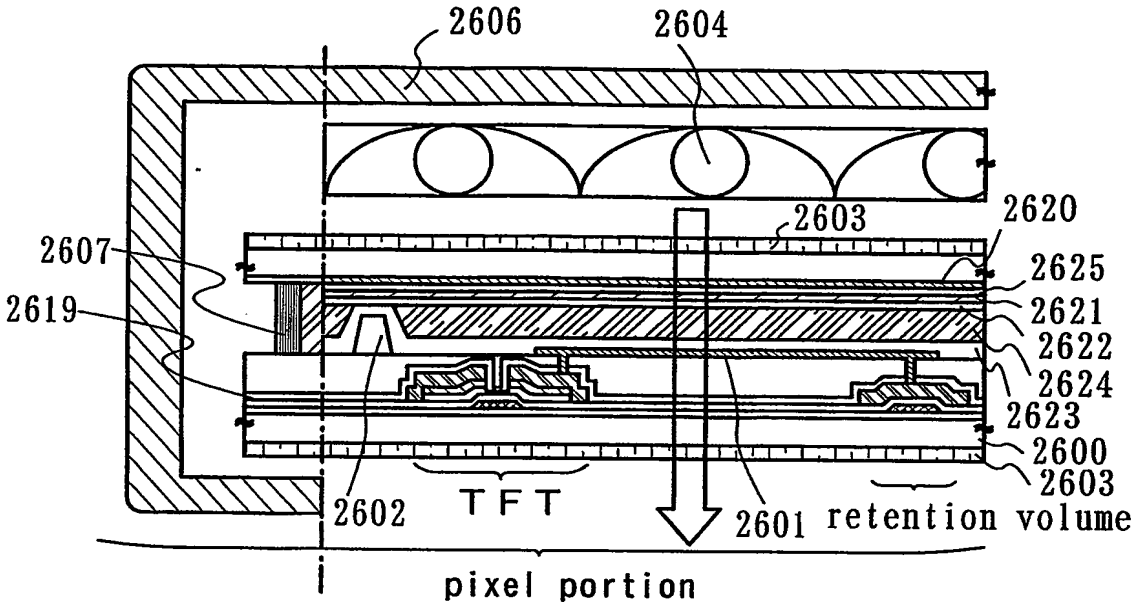

2606
2604
2603
2620
2607
2625
2619
2621
2622
2624
2623
2600
2603
2602
TFT
2601
retention volume
pixel portion

FIG. 30

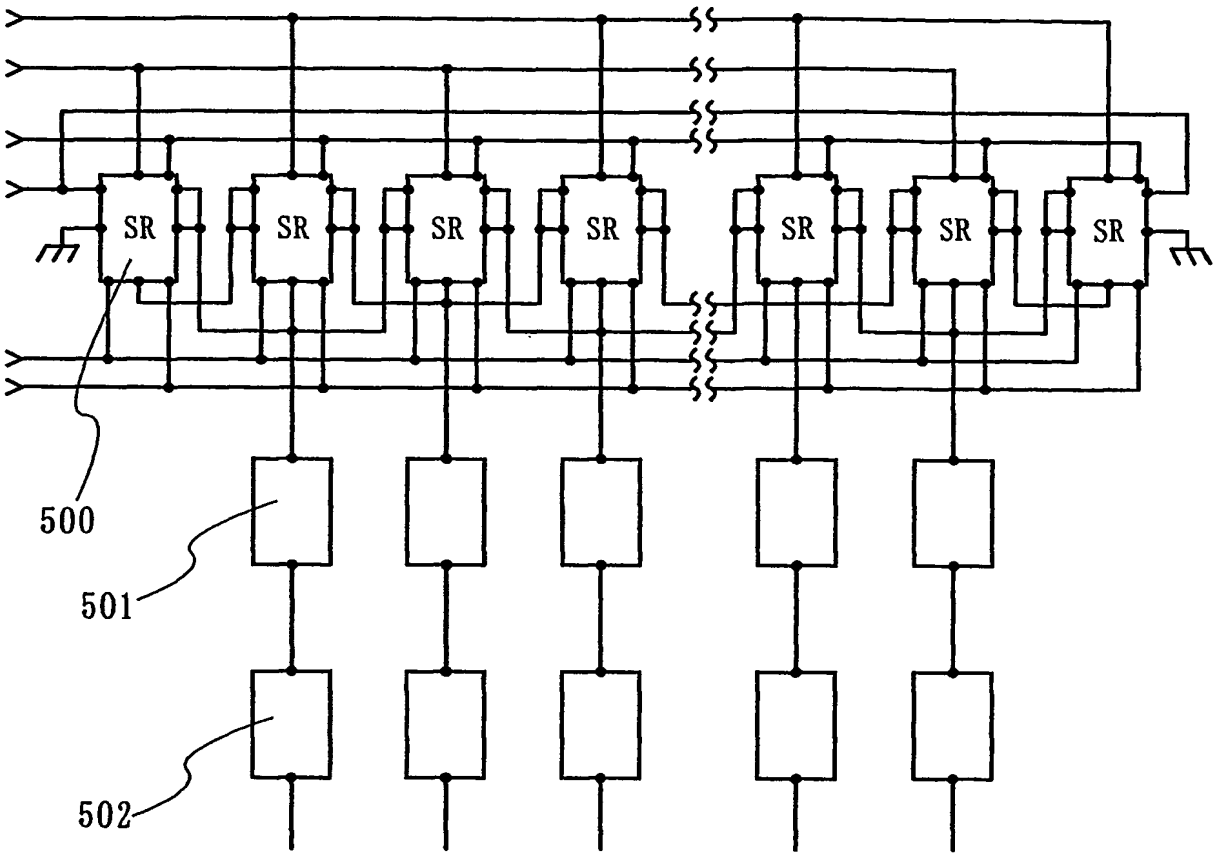


FIG. 31

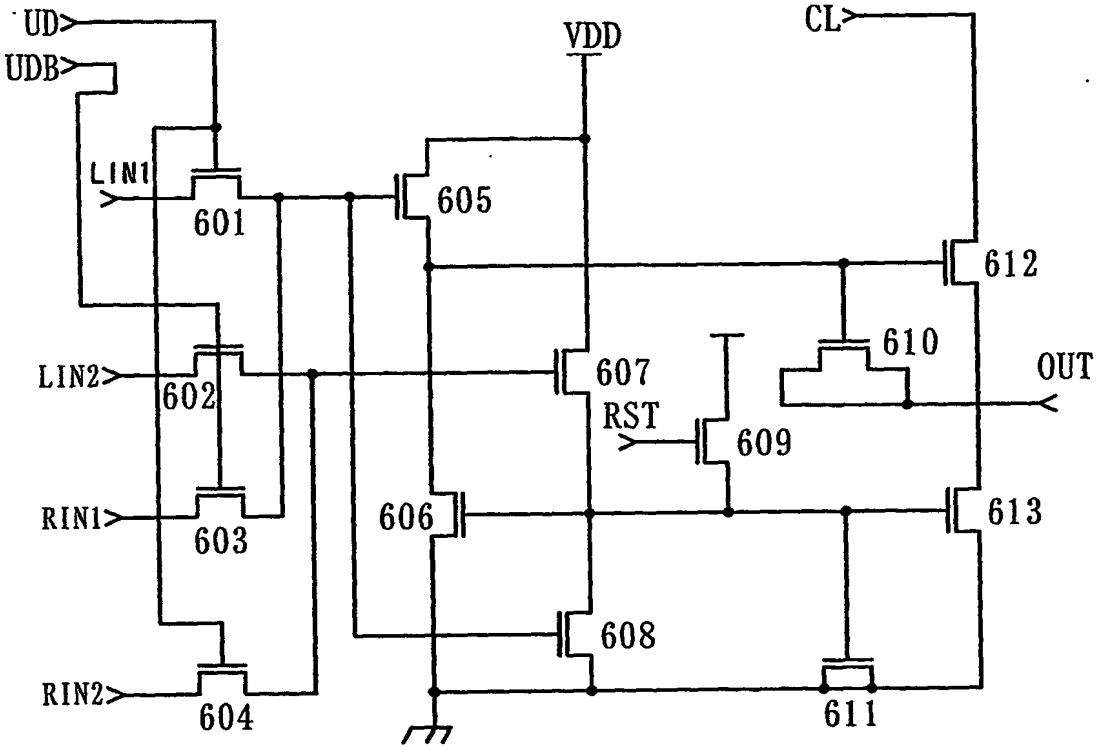

UD
UDB
LIN1
601
605
VDD
CL
612
LIN2
602
607
610
OUT
RST
609
RIN1
603
606
613
608
RIN2
604
611

FIG. 32

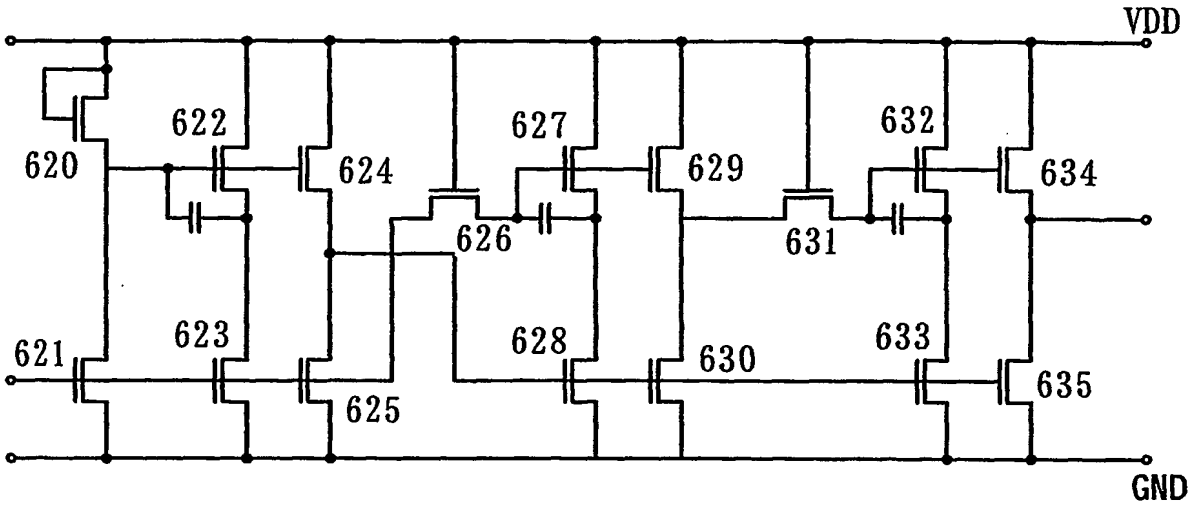

VDD
620
622
624
627
629
632
634
626
631
621
623
625
628
630
633
635
GND

FIG. 33A

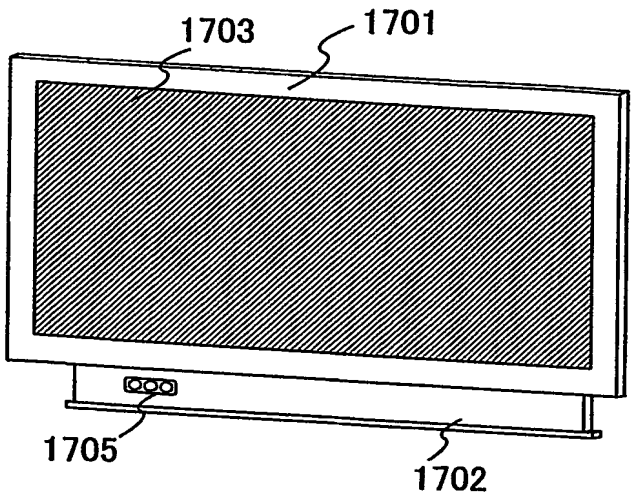


FIG. 33B

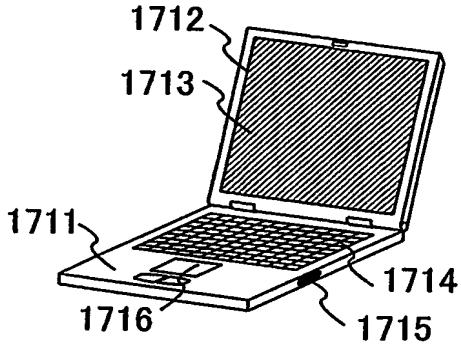


FIG. 33C

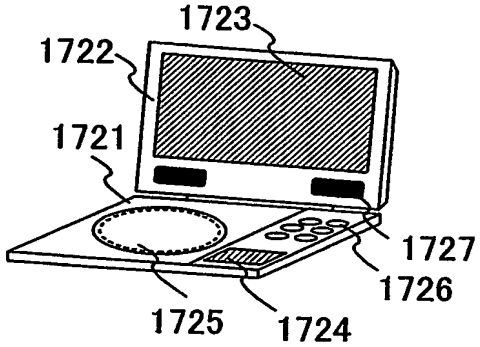
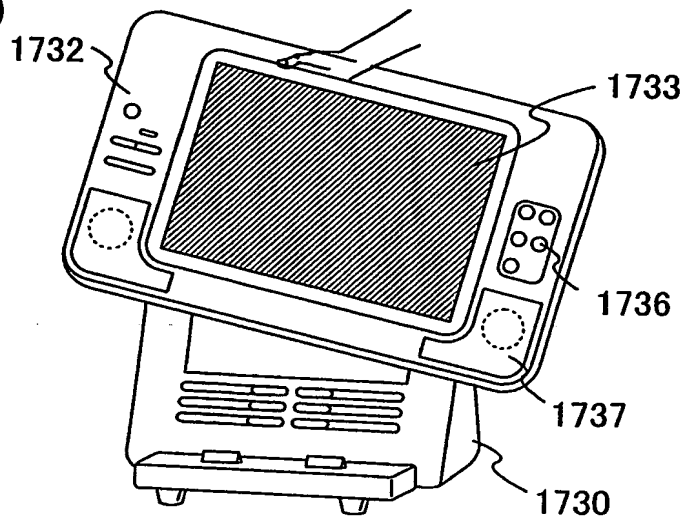


FIG. 33D



EXPLANATION OF REFERENCE

10: substrate, 11: base layer, 12: conductive pattern, 15: gate electrode, 17: leading out electrode, 18: gate insulating film, 19: semiconductor film, 20: semiconductor film, 32; mask, 22: source wiring or drain wiring, 23: source wiring or drain wiring, 24: channel formation region, 25: drain region, 26: source region, 27: protective film, 28: interlayer insulating film, 29: convex portion (pillar), 30: first electrode, 34: bank, 35: sealing substrate, 36: layer containing an organic compound, 37: second electrode, 38: filler, 40: wiring, 41: terminal electrode, 45: anisotropic conductive film, 46: FPC, 220: conductive film pattern, 221: portion irradiated with laser light, 222: source wiring or drain wiring, 223: drain region, 226: source region, 250: conductive pattern, 251: portion irradiated with laser light, 252: source wiring or drain wiring, 253: source wiring or drain wiring, 254: channel formation region, 255: drain region, 256: source region, 260: gate insulating film, 260: gate insulating film, 301: base insulating film, 302: gate electrode, 320: conductive film pattern, 322: source wiring or drain wiring, 323: source wiring or drain wiring, 324; channel formation region, 325: drain region, 326: source region, 401: laser beam directly drawing device, 402: personal computer, 403: laser oscillator, 404: power source, 405: optical system, 406: sound optical modulator, 407: optical system, 408: substrate, 409: substrate, 410: D/A converter, 411: driver, 412: driver, 500: pulse output circuit, 501: buffer circuit, 502: pixel, 601: n-channel TFT, 602: n-channel TFT, 603: n-channel TFT, 604: n-channel TFT, 608: n-channel TFT, 609: n-channel TFT, 610: n-channel TFT, 611: n-channel TFT, 612: n-channel TFT, 613, 620: n-channel TFT, 621: n-channel TFT, 622: n-channel TFT,, 623: n-channel TFT, 624: n-channel TFT, 625: n-channel TFT, 626: n-channel TFT, 627: n-channel TFT, 628: n-channel TFT, 629: n-channel TFT,630: n-channel TFT,631: n-channel TFT, 632: n-channel TFT, 633: n-channel TFT, 634: n-channel TFT, 635: n-channel TFT, 700: substrate, 701: pixel portion, 702: pixel, 703: scanning line side input terminal, 704: signal line side input terminal, 810: substrate, 811: base film, 815: gate electrode, 818: gate insulating film, 822: wiring, 823: wiring, 824: semiconductor film, 825: wiring, 826: n-type semiconductor film, 827: channel protective film, 828: interlayer insulating film, 829: electrode, 830: electrode, 840; terminal electrode, 841: electrode, 910: substrate, 911:

base film, 915: gate wiring, 918: gate insulating layer, 923: source wiring layer, 924: source wiring layer, 925: n-type semiconductor layer, 926: n-type semiconductor layer, 927: semiconductor layer, 928: interlayer insulating film, 929: electrode, 930: electrode, 940: terminal electrode, 941: electrode, 1031: second substrate, 1032: sealant, 1033: liquid crystal, 1034: pixel portion, 1035: first substrate, 1041: first substrate support medium, 1042: second substrate support medium, 1044: window, 1048: lower surface table, 1049: light source, 1110: large substrate, 1111: pixel portion, 1112: sealant, 1113: nozzle scanning direction, 1114: liquid crystal material, 1115: dropped surface, 1116: droplet discharging device, 1118: nozzle, 1119: portion denoted by dotted line, 1120: reverse staggered TFT, 1121: pixel electrode, 1200: sealant, 1201: active matrix substrate, 1202: sealing substrate, 1203: pixel portion, 1204: space, 1205: 1/4λ plate and 1/2λ plate, 1206: polarized plate, 1207: colored layer, 1208: connecting terminal, 1209: FPC, 1210: printed substrate, 1211: pixel driver circuit, 1212: external circuit, 1221: protective film, 1301: driving TFT, 1302: insulating film, 1303: electroluminescent layer, 1304: second electrode, 1305: emitting direction, 1306: both arrows direction, 1310: driver circuit portion, 1311: pixel portion, 1401: switching TFT, 1402: capacitor element, 1403: driving TFT, 1404: current control TFT, 1405: light-emitting element, 1406: TFT, 1410: signal line, 1411: power line, 1412: power line, 1413: power line, 1414: scanning line, 1415: power line, 1441: switching TFT, 1442: capacitor element, 1443: driving TFT, 1444: light-emitting element, 1445: TFT, 1450: signal line, 1451: power line, 1452: power line, 1453: scanning line, 1454: scanning line, 1500: large substrate, 1503: region, 1504: imaging means, 1505a: head, 1505b: head, 1505c: head, 1507: stage, 1511: marker, 1600: substrate, 1601: pixel region, 1602: scanning line driver circuit, 1604a, 1604b, and 1605a: driver circuit, 1605b: driver circuit, 1701: housing, 1702: support medium, 1703: display portion, 1705: video input terminal, 1711: main body, 1712: housing, 1713: display portion, 1714: key board, 1715: external connecting port, 1716: pointing mouse, 1721: main body, 1722: housing, 1723: display portion A, 1724: display portion B, 1725: recording medium reading portion, 1726: operation keys, 1727: speaker portion, 1730: charger, 1732: housing, 1733: display portion, 1736: operation keys, 1737: speaker portion, 1800: active matrix substrate, 1801: opposing substrate, 1802: sealant, 1803:

pixel region, 1804: drying agent, 1805: source wiring, 1806: gate wiring, 1807: pixel, 1811: pixel, 1812: pixel electrode, 1814: drying agent, 2010: substrate, 2011: base substrate, 2012: conductive film pattern, 2015: gate wiring, 2018: gate insulating film, 2019: semiconductor film, 2020: semiconductor film, 2021: mask, 2022: source wiring or drain wiring, 2023: source wiring or drain wiring, 2024: channel formation region, 2025: drain region, 2026: source region, 2027: protective film, 2028: interlayer insulating film, 2029: convex portion (pillar), 2030: pixel electrode, 2034a: oriented film, 2034b: oriented film, 2035: opposing substrate, 2036a: colored layer, 2036b: light-shielding film (black matrix), 2037: overcoat layer, 2038, 2039: liquid crystal, 2040: wiring, 2045: anisotropic conductive layer, 2046: FPC, 2120: conductive film pattern, 2121: portion irradiated with laser light, 2122: source wiring or drain wiring, 2123: source wiring or drain wiring, 2124: channel formation region, 2125: drain region, 2126: source region, 2150: conductive pattern, 2151: portion irradiated with laser light, 2152: source wiring or drain wiring, 2153: source wiring or drain wiring, 2154: channel formation region, 2155: drain region, 2156: source region, 2160: gate insulating film, 2201: base insulating film, 2202: gate electrode, 2220: conductive film pattern, 2222: source wiring or drain wiring, 2223: source wiring or drain wiring, 2224: channel formation region, 2225: drain region, 2226: source region, 2310: substrate, 2311: base insulating, 2315: gate electrode, 2318: gate insulating film, 2322: wiring, 2323: wiring, 2324: semiconductor film, 2325: n-type semiconductor film, 2326: n-type semiconductor film, 2627: channel protective film, 2328: interlayer insulating film, 2329: electrode, 2330: electrode, 2340: terminal electrode, 2341: electrode, 2410, 2411: base film, 2415: gate wiring, 2418: gate insulating layer, 2423: source wiring layer, 2424: drain wiring layer, 2425: n-type semiconductor, 2426: n-type semiconductor, 2427: semiconductor layer, 2428: interlayer insulating film, 2429: electrode, 2430: electrode, 2440: terminal electrode, 2441: electrode, 2501: substrate, 2504: pixel portion, 2505: FPC, 2506: opposing substrate, 2507: sealant, 2511: substrate, 2512: source signal line driver circuit, 2513: gate signal line driver circuit, 2514: pixel portion, 2515: FPC, 2516: opposing substrate, 2517: sealant, 2518: second sealant, 2600: substrate, 2601: pixel electrode, 2602: spacer, 2603: polarized plate, 2604: backlight valve, 2606: cover, 2607: sealant, 2620: CF, 2621:

opposing electrode, 2622: oriented film, 2623: oriented film, 2624: liquid crystal layer, 2625: planarized film.